=> file reg FILE 'REGISTRY' ENTERED AT 15:23:51 ON 01 OCT 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2003 American Chemical Society (ACS)

=> display history full l1-

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FILE 'REGISTRY' ENTERED AT 14:06:18 ON 01 OCT 2003
                E NITRIC OXIDE/CN
              1 SEA "NITRIC OXIDE"/CN
L1
                E NITROGEN DIOXIDE/CN
              1 SEA "NITROGEN DIOXIDE"/CN
L2
                E HYDROGEN PEROXIDE/CN
              1 SEA "HYDROGEN PEROXIDE"/CN
L3
     FILE 'HCA' ENTERED AT 14:10:36 ON 01 OCT 2003
           2893 SEA (OXIDIZ? OR OXIDIS? OR OXIDAT? OR OXIDN#)(3A)(L1 OR
L4
                NITRIC#(W)OXIDE# OR NO(A)(GAS## OR GASEOUS? OR GASIF? OR
                STREAM? OR FLOW OR FLOWS OR FLOWED OR FLOWING#))
         135015 SEA L2 OR NITROGEN#(W)DIOXIDE# OR NO2
L5
         166247 SEA L3 OR HYDROGEN#(A) PEROXIDE# OR H2O2
L6
             36 SEA L4 AND L5 AND L6
L7
          74835 SEA L1
L8
             31 SEA L7 AND L8
L9
          19890 SEA (CAT# OR CATALY?)(2A)(COAT? OR FILM? OR LAYER?)
L10
              0 SEA L7 AND L10
L11
            539 SEA L8 AND L5 AND L6
L12
               2 SEA L12 AND L10
L13
     FILE 'REGISTRY' ENTERED AT 14:20:22 ON 01 OCT 2003
                E IRON/CN
               1 SEA IRON/CN
L14
                E CHROMIUM/CN
               1 SEA CHROMIUM/CN
L15
                 E COPPER/CN
               1 SEA COPPER/CN
L16
                 E PLATINUM/CN
               1 SEA PLATINUM/CN
L17
                 E SILVER/CN
               1 SEA SILVER/CN
L18
                 E PALLADIUM/CN
               1 SEA PALLADIUM/CN
L19
     FILE 'LCA' ENTERED AT 14:22:34 ON 01 OCT 2003
             508 SEA (L14 OR L15 OR L16 OR L17 OR L18 OR L19 OR IRON# OR
L20
                 FE OR CHROMIUM# OR CR OR COPPER# OR CU OR PLATINUM# OR
                 PT OR SILVER# OR AG OR PALLADIUM# OR PD) (2A) (FILM? OR
                 COAT? OR LAYER?)
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FILE 'HCA' ENTERED AT 14:25:53 ON 01 OCT 2003
        198358 SEA (L14 OR L15 OR L16 OR L17 OR L18 OR L19 OR IRON# OR
L21
                FE OR CHROMIUM# OR CR OR COPPER# OR CU OR PLATINUM# OR
                PT OR SILVER# OR AG OR PALLADIUM# OR PD)(2A)(FILM? OR
                COAT? OR LAYER?)
              2 SEA L7 AND L21
L22
              3 SEA L12 AND L21
L23
     FILE 'REGISTRY' ENTERED AT 14:26:30 ON 01 OCT 2003
                E SILVER OXIDE/CN
              2 SEA "SILVER OXIDE"/CN
L24
                E IRON OXIDE/CN
              4 SEA "IRON OXIDE"/CN
L25
                E RUTHENIUM OXIDE/CN
              1 SEA "RUTHENIUM OXIDE"/CN
L26
                E COPPER FERRITE/CN
              2 SEA "COPPER FERRITE"/CN
L27
                E MAGNESIUM OXIDE/CN
              1 SEA "MAGNESIUM OXIDE"/CN
L28
     FILE 'HCA' ENTERED AT 14:29:45 ON 01 OCT 2003
           6063 SEA L24
L29
          79928 SEA L25
L30
          1684 SEA L26
L31
           1053 SEA L27
L32
          83781 SEA L28
L33
              4 SEA L7 AND ((L29 OR L30 OR L31 OR L32 OR L33))
L34
     FILE 'LCA' ENTERED AT 14:31:13 ON 01 OCT 2003
           1074 SEA (SILVER# OR AG) (W) (OXIDE# OR MONOXIDE#) OR AG20 OR
L35
                AGO/IT OR (IRON# OR FE)(W)(OXIDE# OR DIOXIDE# OR
                TRIOXIDE#) OR FEO OR FE2O3 OR (RUTHENIUM# OR RU)(W)(OXIDE
                 # OR DIOXIDE# OR TETROXIDE# OR TETRAOXIDE#) OR RUO2 OR
                 RUO4 OR QUARTZ# OR (MOLYBDENUM# OR MO) (2A) GLASS?
            483 SEA SPINEL# OR (COPPER# OR CU) (A) FERRITE# OR (MAGNESIUM#
L36
                 OR MG) (W) (OXIDE# OR MONOXIDE#) OR MGO
     FILE 'HCA' ENTERED AT 14:42:29 ON 01 OCT 2003
           25285 SEA ((L29 OR L30 OR L31 OR L32 OR L33) OR L35 OR
L37
                 L36)(2A)(COAT? OR FILM? OR LAYER?)
               1 SEA L7 AND L37
L38
               5 SEA L7 AND (L35 OR L36)
L39
              21 SEA L12 AND ((L29 OR L30 OR L31 OR L32 OR L33))
L40
              3 SEA L12 AND L37
L41
              25 SEA L12 AND (L35 OR L36)
L42
              18 SEA L40 AND L42
L43
     FILE 'REGISTRY' ENTERED AT 14:56:16 ON 01 OCT 2003
                 E ALUMINA/CN
               1 SEA ALUMINA/CN
L44
```

FILE 'HCA' ENTERED AT 14:57:22 ON 01 OCT 2003

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L45
         659749 SEA GLASS?
         450657 SEA L44 OR (ALUMINUM# OR AL)(W)(OXIDE# OR TRIOXIDE#) OR
L46
                ALUMINA# OR AL2O3
              0 SEA L7 AND L45
L47
              5 SEA L7 AND L46
L48
              8 SEA L12 AND L45
L49
             21 SEA L12 AND L46
L50
             16 SEA L40 AND L50
L51
             14 SEA L42 AND L50
L52
             21 SEA L13 OR L22 OR L23 OR L34 OR L38 OR L39 OR L41 OR L48
L53
                 OR L49
             13 SEA (L43 OR L51 OR L52) NOT L53
L54
             28 SEA (L7 OR L9) NOT (L53 OR L54)
L55
              9 SEA (L40 OR L42 OR L50) NOT (L53 OR L54 OR L55)
L56
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FILE 'REGISTRY' ENTERED AT 15:23:51 ON 01 OCT 2003

=> file hca FILE 'HCA' ENTERED AT 15:24:03 ON 01 OCT 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d 153 1-21 cbib abs hitstr hitind

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L53 ANSWER 1 OF 21 HCA COPYRIGHT 2003 ACS on STN
139:45133 Methods of forming roughened layers of
platinum for use in capacitors. Marsh, Eugene P. (Micron
Technology, Inc., USA). U.S. US 6583022 B1 20030624, 7 pp.
(English). CODEN: USXXAM. APPLICATION: US 1998-141840 19980827.
```

The invention relates to a method of forming roughened layers of platinum for use in capacitors. The method consists of the steps of (i) providing a substrate within a reaction chamber; (ii) flowing an oxidizing gas into the reaction chamber; (iii) flowing a platinum precursor into the reaction chamber and depositing platinum from the platinum precursor over the substrate in the presence of the oxidizing gas; and (iv) maintaining a temp. within the reaction chamber of 0-300.degree. during the depositing.

7722-84-1, Hydrogen peroxide, processes
10102-43-9, Nitrogen monoxide, processes 10102-44-0
, Nitrogen oxide (NO2), processes
(oxidizing agent; methods of forming roughened

layers of platinum for use in capacitors)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

```
10102-43-9 HCA
RN
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
CN
N = 0
     10102-44-0 HCA
RN
     Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
CN
O - N = O
     ICM H01L021-20
IC
     ICS H01L021-44
     438398000; 438964000; 438686000
NCL
     76-2 (Electric Phenomena)
CC
     Section cross-reference(s): 56
     roughened layer platinum capacitor
ST
     Surface roughness
IT
        (Pt film with; methods of forming roughened
        layers of platinum for use in capacitors)
     Adhesion promoters
IT
     Capacitor electrodes
     Capacitors
        (methods of forming roughened layers of
        platinum for use in capacitors)
     Controlled atmospheres
IT
        (oxidizing; methods of forming roughened layers of
        platinum for use in capacitors)
                                7440-04-2, Osmium, uses 7440-05-3,
     7439-88-5, Iridium, uses
IT
                       7440-16-6, Rhodium, uses
                                                  7440-18-8,
     Palladium, uses
                       7440-22-4, Silver, uses
                                                  11107-69-0
     Ruthenium, uses
                                      12030-49-8, Iridium oxide
     11107-71-4, Platinum, rhodium
                                       12036-10-1, Ruthenium
     12036-02-1, Osmium oxide (OsO2)
                     12137-27-8, Rhodium oxide (RhO2)
     oxide (RuO2)
                  25583-20-4, Titanium nitride (TiN)
                                                        37186-87-1
     12779-05-4
                  66174-72-9
     37186-93-9
         (adhesion layer; methods of forming roughened
        layers of platinum for use in capacitors)
     65353-51-7, Platinum Bis(hexafluoroacetylacetonate) 121309-87-3,
IT
     cis-Bis(isocyanomethane)dimethylplatinum
         (methods of forming roughened layers of
        platinum for use in capacitors)
     7446-11-9, Sulfur trioxide, processes 7722-84-1,
IT
     Hydrogen peroxide, processes 7782-44-7, Oxygen,
                  10024-97-2, Nitrous oxide, processes
                                                         10028-15-6,
     processes
     Ozone, processes 10102-43-9, Nitrogen monoxide, processes
     10102-44-0, Nitrogen oxide (NO2), processes
      12033-49-7, Nitrogen oxide (NO3)
         (oxidizing agent; methods of forming roughened
         layers of platinum for use in capacitors)
 IT
      7440-06-4P, Platinum, uses
```

(roughened film; methods of forming roughened layers of platinum for use in capacitors) 1271-07-4, Cyclopentadienyl trimethylplatinum 15170-57-7, Platinum IT 19529-53-4, Platinum tetrakis(trifluorophosphine) acetylacetonate 25478-60-8, Dicarbonyldichloroplatinum 94442-22-5, Methylcyclopentadienyl trimethylplatinum (vapor deposition precursor; methods of forming roughened layers of platinum for use in capacitors) ANSWER 2 OF 21 HCA COPYRIGHT 2003 ACS on STN L53 138:329361 Deposition method and apparatus of a silicon contg. film at a low temp. while restricting charge-up of a substrate, and a semiconductor device including the film. Ohtake, Naoto (Japan). U.S. Pat. Appl. Publ. US 2003077883 Al 20030424, 12 pp. (English). CODEN: USXXCO. APPLICATION: US 2002-230406 20020829. PRIORITY: JP 2001-272617 20010907; JP 2002-200451 20020709. The deposition method is that reactive gas is made to pass through · AB communication holes and guided toward downstream of the communication holes after the gas is exposed to surface wave of microwave, and it is reacted with Si compd. gas to deposit a Si-contg. film on a substrate arranged in the downstream. 7722-84-1, Hydrogen peroxide, processes IT 10102-43-9, Nitric oxide, processes 10102-44-0, Nitrogen dioxide, processes (reactive gas; deposition method and app. of silicon contg. film at low temp. while restricting charge-up of substrate) RN 7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CN HO-OH RN10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CNN = O10102-44-0 HCA RNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN

IC ICM C30B001-00
ICS H01L021-20; H01L021-36
NCL 438478000
CC 75-1 (Crystallography and Liquid Crystals)
IT Glass substrates
Vapor deposition apparatus
Vapor deposition process
(deposition method and app. of silicon contg. film at low temp.

0 - N = 0

```
while restricting charge-up of substrate)
     7722-84-1, Hydrogen peroxide, processes
IT
                                    10024-97-2, Nitrogen oxide (N2O),
     7782-44-7, Oxygen, processes
    processes 10102-43-9, Nitric oxide, processes
     10102-44-0, Nitrogen dioxide, processes
     12033-49-7, Nitrogen trioxide
        (reactive gas; deposition method and app. of silicon contg. film
        at low temp. while restricting charge-up of substrate)
    ANSWER 3 OF 21 HCA COPYRIGHT 2003 ACS on STN
138:279720 Solvated ruthenium precursors for direct liquid injection of
     ruthenium and ruthenium oxide and method of using same. Marsh,
     Eugene P.; Uhlenbrock, Stefan (Micron Technology, Inc., USA).
     US 6541067 B1 20030401, 7 pp., Cont.-in-part of U.S. Ser. No.
     140,878. (English). CODEN: USXXAM. APPLICATION: US 2000-506962
     20000218. PRIORITY: US 1998-140878 19980827; US 1998-140932
     19980827.
     A method is provided for forming a film of Ru or Ru oxide to the
AB
     surface of a substrate by employing the techniques of CVD to decomp.
     Ru precursor formulations. The Ru precursor formulations of the
     present invention include a Ru precursor compd. and a solvent
     capable of solubilizing the Ru precursor compd. A method is further
     provided for making a vaporized Ru precursor for use in the CVD of
     Ru and Ru-contg. materials onto substrates, wherein a Ru precursor
     formulation having a Ru-contg. precursor compd. and a solvent
     capable of solubilizing the Ru-contg. precursor compd. is vaporized.
     11113-84-1, Ruthenium oxide
IT
        (films; method of forming Ru or Ru
        oxide films on semiconductor substrate by CVD
        using solvated ruthenium precursors)
     11113-84-1 HCA
RN
                           (CA INDEX NAME)
     Ruthenium oxide (9CI)
CN
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
     7722-84-1, Hydrogen peroxide, processes
     10102-43-9, Nitrogen oxide (NO), processes
     10102-44-0, Nitrogen dioxide, processes
         (oxidizing agent; method of forming Ru or Ru
        oxide films on semiconductor substrate by CVD
        using solvated ruthenium precursors)
     7722-84-1 HCA
RN
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
HO-OH
     10102-43-9 HCA
RN
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
```

10102-44-0 HCA RN

CN

N=== 0

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

0- N=0

IC ICM C23C016-16

NCL 427252000; 427255310; 427901000; 438681000; 438686000; 438758000; 438778000

CC 76-3 (Electric Phenomena)
Section cross-reference(s): 75

IT Peroxides, processes

(org., oxidizing agent; method of forming Ru or Ru

oxide films on semiconductor substrate by CVD

using solvated ruthenium precursors)

IT 11113-84-1, Ruthenium oxide
(films; method of forming Ru or Ru
oxide films on semiconductor substrate by CVD
using solvated ruthenium precursors)

7440-18-8, Ruthenium, processes
(films; method of forming Ru or Ru oxide
films on semiconductor substrate by CVD using solvated
ruthenium precursors)

7446-09-5, Sulfur dioxide, processes 7446-11-9, Sulfur trioxide, processes 7722-84-1, Hydrogen peroxide, processes 7732-18-5, Water, processes 7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes 10102-43-9, Nitrogen oxide (NO), processes 10102-44-0, Nitrogen dioxide, processes

(oxidizing agent; method of forming Ru or Ru oxide films on semiconductor substrate by CVD using solvated ruthenium precursors)

IT 12108-25-7

(precursor; method of forming Ru or Ru oxide films on semiconductor substrate by CVD using solvated ruthenium precursors)

IT 109-66-0, Pentane, uses 110-54-3, Hexane, uses 123-86-4, Butyl acetate 142-82-5, Heptane, uses (solvent; method of forming Ru or Ru oxide films on semiconductor substrate by CVD using solvated ruthenium precursors)

L53 ANSWER 4 OF 21 HCA COPYRIGHT 2003 ACS on STN

138:9831 Low dielectric constant material and method of processing by CVD. O'Neill, Mark Leonard; Peterson, Brian Keith; Vincent, Jean Louise; Vrtis, Raymond Nicholas (Air Products and Chemicals, Inc., USA). Eur. Pat. Appl. EP 1260606 A2 20021127, 20 pp. DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,

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MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR. (English). CODEN: EPXXDW. APPLICATION: EP 2002-10229 20020516. PRIORITY: US 2001-863150 20010523.
```

Organofluorosilicate **glass** films contain both org. species and inorg. fluorines, exclusive of significant amts. of fluorocarbon species. Preferred films are SivOwCxHyFz, where v+w+x+y+z = 100%, v is 10-35 at.%, w is 10-65 at.% y is 10-50 at.%, x is 1-30 at.%, z is 0.1-15 at.%, and x/z is optionally >0.25, wherein substantially none of the fluorine is bonded to the C. A CVD method includes: (a) providing a substrate within a vacuum chamber; (b) introducing into the vacuum chamber gaseous reagents including a fluorine-providing gas, an oxygen-providing gas and at least one precursor gas selected from an organosilane and an organosiloxane; and (c) applying energy to the gaseous reagents in the chamber to induce reaction of the gaseous reagents and to form the film on the substrate.

7722-84-1, Hydrogen peroxide, processes
10102-43-9, Nitrogen oxide (NO), processes
10102-44-0, Nitrogen dioxide, processes
(CVD method of producing organofluorosilicate glass films having low dielec. const.)

RN 7722-84-1 HCA CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N = O

CC

IC ICM C23C016-30 ICS C23C016-40; C03C003-062; H01L021-316

75-1 (Crystallography and Liquid Crystals) Section cross-reference(s): 76

ST low dielec const organofluorosilicate glass film CVD

IT Silanes

Siloxanes (nonpolymeric)

(CVD method of producing organofluorosilicate glass films having low dielec. const.)

IT Fluoride glasses

Silicate **glasses**(fluorosilicate, organo-, carbon-contg.; CVD method of producing organofluorosilicate **glass** films having low dielec. const.)

```
IT
     Fluoride glasses
     Silicate glasses
        (fluorosilicate; low dielec. const. organofluorosilicate
        glass films being capable of adhering to)
     Integrated circuits
IT
        (low dielec. const. organofluorosilicate glass films as
        component layers in)
     Antireflective films
IT
     Photoresists
     Porous materials
        (low dielec. const. organofluorosilicate glass films
        being capable of adhering to)
     Metals, miscellaneous
IT
     Polymers, miscellaneous
        (low dielec. const. organofluorosilicate glass films
        being capable of adhering to)
     Silicate glasses
IT
        (organo-; low dielec. const. organofluorosilicate glass
        films being capable of adhering to)
     75-76-3, Tetramethylsilane 78-10-4, Tetraethoxysilane
                                                                 78-62-6,
IT
                             353-66-2, Difluorodimethylsilane
     Dimethyldiethoxysilane
     358-60-1, Fluorotriethoxysilane 373-74-0, Methyltrifluorosilane
     420-56-4, Fluorotrimethylsilane 542-91-6, Diethylsilane
                               766-08-5, Methylphenylsilane
     694-53-1, Phenylsilane
                    993-07-7, Trimethylsilane 998-30-1, Triethoxysilane
     Methylsilane
                                 1112-39-6, Dimethyldimethoxysilane
     1111-74-6, Dimethylsilane
     1529-17-5, Trimethylphenoxysilane 2031-62-1, Methyldiethoxysilane 2488-01-9, 1,4-Bis(dimethylsilyl)benzene 2551-62-4, Sulfur
                                                          5654-04-6
     hexafluoride 2814-79-1, Ethylsilane
                                            4364-07-2
     5833-47-6, 1,1-Dimethyl-1-sila-2-oxacyclohexane
                                                        7381-30-8,
     1,2-Bis(trimethylsiloxy)ethane 7637-07-2, Boron fluoride (BF3),
                 7664-39-3, Hydrogen fluoride, processes
     processes
     7722-84-1, Hydrogen peroxide, processes
                                       7782-44-7, Oxygen, processes
     7782-41-4, Fluorine, processes
                                           7783-60-0, Sulfur fluoride
     7783-54-2, Nitrogen fluoride (NF3)
             7783-61-1, Silicon fluoride (SiF4)
                                                   7787-71-5, Bromine
                       7790-91-2, Chlorine fluoride (ClF3)
                                                              10024-97-2,
     fluoride (BrF3)
     Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes
     10102-43-9, Nitrogen oxide (NO), processes
     10102-44-0, Nitrogen dioxide, processes
                                                        13537-33-2 .
     10544-72-6, Nitrogen oxide (N2O4)
                                          13465-71-9
     13637-87-1, Nitrogen chloride fluoride (NClF2)
                                                       13824-36-7
                                                       17082-61-0,
     14857-34-2, Dimethylethoxysilane
                                        14879-83-5
                                           18139-76-9, Phenoxysilane
     1,2-Bis(trimethylsiloxy)cyclobutene
     18162-96-4, Cyclohexylsilane 18165-85-0, tert-Butylsilane
                   476608-55-6
     25711-12-0
         (CVD method of producing organofluorosilicate glass
         films having low dielec. const.)
     409-21-2, Silicon carbide (SiC), miscellaneous
                                                        7440-21-3, Silicon,
IT
     miscellaneous 7631-86-9, Silicon oxide (SiO2), miscellaneous
     12033-89-5, Silicon nitride (Si3N4), miscellaneous
         (low dielec. const. organofluorosilicate glass films
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being capable of adhering to)

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ANSWER 5 OF 21 HCA COPYRIGHT 2003 ACS on STN
136:320460 Microelectrodes in artificial synapses: a study of oxidative
     stress at the cellular level. Amatore, Christian; Arbault,
     Stephane; Bruce, Delphine; De Oliveira, Pedro; Erard, Marie;
     Vuillaume, Monique (Dept. de Chimie UMR CNRS 8640 "Pasteur", Ecole
     Normale Superieure, Paris, 75231, Fr.). Portugaliae Electrochimica Acta, 19(3/4), 145-163 (English) 2001. CODEN: PEACEZ. ISSN:
     0872-1904. Publisher: Portuguese Electrochemical Society.
     Platinized carbon microelectrodes (.apprx.10 .mu.m diam.),
AB
     positioned close (.apprx.5 .mu.m) to the cell membrane of a human
     fibroblast, the ensemble constituting a semi-artificial synapse, are
     used to monitor events at the cellular level. A few tens of
     femtomoles of reactive oxygen species produced and emitted by the
     cell upon mech. pricking with a glass micropipette
     (.apprx.1 .mu.m diam.) are released into the liq. film of some
     hundred femtoliters comprised between the cytoplasmic membrane and
     the electrode surface, leading to a sudden and drastic rise in their
     concns. (in the order of several micromoles). This oxidative
     stress-type response aims at disarming the aggressor and is thought
     to be shared by many (if not all) eukaryotic cells. This method
     allows to detect a real time and quantify the species constituting
     the oxidative burst cocktail: hydrogen peroxide,
     H2O2, peroxynitrite, ONO2, nitrogen monoxide, NOO, and
     nitrite, NO2. They are likely to derive ultimately from
     superoxide anion, 020-, and nitrogen monoxide, NOO, synthesized by
     NADPH oxidase and NO synthase enzyme systems, resp. By placing the
     microelectrode at different positions about the injured area of the
     cell membrane, it was concluded that the signals correspond to a
     spherical diffusion of the emitted electroactive species from a
     point-source.
     7722-84-1, Hydrogen peroxide, biological
IT
     studies 10102-43-9, Nitric oxide, biological studies
        (microelectrodes in artificial synapses in a study of oxidative
        stress at the cellular level)
     7722-84-1 HCA
RN
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
HO-OH
```

10102-43-9 HCA RN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CN

N = O

CC 4-1 (Toxicology) Section cross-reference(s): 9, 13 7722-84-1, Hydrogen peroxide, biological IT7782-44-7D, Oxygen, reactive species 10102-43-9, Nitric oxide, biological studies 11062-77-4, Superoxide 14797-65-0, Nitrite, biological studies 19059-14-4, Peroxynitrite (microelectrodes in artificial synapses in a study of oxidative stress at the cellular level)

ANSWER 6 OF 21 HCA COPYRIGHT 2003 ACS on STN L53 135:234817 Deposition and annealing of multicomponent ZrSnTiOx and HfSnTiOx oxide thin films using solventless liquid mixture of precursors. Senzaki, Yoshihide; Hochberg, Arthur Kenneth; Roberts, David Allen; Norman, John Anthony Thomas; Fleming, Robert Mclemore; Alers, Glenn Baldwin (Air Products and Chemicals, Inc., USA; Lucent Technologies Inc.). Eur. Pat. Appl. EP 1132494 A2 20010912, 9 pp. DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO. (English). CODEN: EPXXDW. APPLICATION: EP 2001-105786 20010308. PRIORITY: US

2000-522634 20000310.

Complex mixed metal contg. thin films can be deposited by CVD from AΒ liq. mixts. of metal complexes without solvent by direct liq. injection and by other precursor dispersing method such as aerosol delivery with subsequent annealing to improve elec. properties of the deposited films. This process has potential for com. success in microelectronics device fabrication of dielecs., ferroelecs., barrier metals/electrodes, superconductors, catalysts, and protective coatings. Application of this process, particularly the CVD of ZrSnTiOx (Zr Sn titanate, or ZTT) and HfSnTiOx (Hf Sn titanate, or HTT) thin films was studied successfully.

10102-44-0, Nitrogen oxide (no2), processes IT(deposition and annealing of ZrSnTiOx and HfSnTiOx oxide films using solventless liq. mixt. of precursors and oxygen contg. reactant of)

RN 10102-44-0 HCA

Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN

0 - N = 0

7722-84-1, Hydrogen peroxide, processes IT 10102-43-9, Nitrogen oxide (NO), processes (deposition and annealing of multicomponent ZrSnTiOx and HfSnTiOx oxide thin films using solventless liq. mixt. of precursors and annealing gas of)

7722-84-1 HCA RN

Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CN

HO—OH

HCA 10102-43-9 RNNitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CN

N == O

IC ICM C23C016-18

ICS C23C016-40; C30B025-14

CC 76-3 (Electric Phenomena)

Section cross-reference(s): 75

- 10102-44-0, Nitrogen oxide (no2), processes (deposition and annealing of ZrSnTiOx and HfSnTiOx oxide films using solventless liq. mixt. of precursors and oxygen contg. reactant of)
- 7440-37-1, Argon, processes 7440-59-7, Helium, processes
 7722-84-1, Hydrogen peroxide, processes
 7727-37-9, Nitrogen, processes 7732-18-5, Water, processes
 7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes 10102-43-9,

Nitrogen oxide (NO), processes (deposition and annealing of multicomponent ZrSnTiOx and HfSnTiOx oxide thin films using solventless liq. mixt. of precursors and annealing gas of)

- L53 ANSWER 7 OF 21 HCA COPYRIGHT 2003 ACS on STN
 133:128678 Organometallic deposition of dielectric layers using
 supercritical fluids such as CO2 in semiconductor device
 fabrication. Morita, Kiyoyuki; Ohtsuka, Takashi; Ueda, Michihito
 (Matsushita Electric Industrial Co., Ltd., Japan). Eur. Pat. Appl.
 EP 1024524 A2 20000802, 32 pp. DESIGNATED STATES: R: AT, BE, CH,
 DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV,
 FI, RO. (English). CODEN: EPXXDW. APPLICATION: EP 2000-101398
 20000125. PRIORITY: JP 1999-18597 19990127; JP 1999-104873
 19990413.
- As semiconductor substrate is placed within a housing. By supplying organometallic complexes and CO2 in a supercrit. state into the housing, a BST thin film is formed on a Pt thin film, while at the same time, C compds., which are produced when the BST thin film is formed, are removed. The soly. of C compds. in the supercrit. CO2 is very high, and yet the viscosity of the supercrit. CO2 is low. Accordingly, the C compds. are removable efficiently from the BST thin film. An oxide or nitride film may also be formed by performing oxidn. or nitriding at a low temp. using H2O in a supercrit. or subcrit. state, for example.
- 7722-84-1, Hydrogen peroxide, uses
 10102-43-9, Nitric oxide, uses
 10102-44-0, Nitrogen dioxide, uses
 (oxidizing agent; organometallic deposition of dielec.
 layers using supercrit. fluids such as carbon dioxide in semiconductor device fabrication)
- RN 7722-84-1 HCA CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

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но-он
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RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

0 - N = 0

IC ICM H01L021-316

CC 76-3 (Electric Phenomena)

7722-84-1, Hydrogen peroxide, uses
10028-15-6, Ozone, uses 10102-43-9, Nitric
oxide, uses 10102-44-0, Nitrogen
dioxide, uses

(oxidizing agent; organometallic deposition of dielec. layers using supercrit. fluids such as carbon dioxide in semiconductor device fabrication)

L53 ANSWER 8 OF 21 HCA COPYRIGHT 2003 ACS on STN

- 133:25620 Low temperature CVD processes for preparing ferroelectric films using bi alkoxides. Hintermaier, Frank S.; Van, Buskirk Peter C.; Roeder, Jeffrey F.; Hendrix, Bryan C.; Baum, Thomas H.; Desrochers, Debra A. (Infineon Technologies A.-G., Germany; Advanced Technology Materials, Inc.). PCT Int. Appl. WO 2000034549 A2 20000615, 39 pp. DESIGNATED STATES: W: CN, JP, KR; RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE. (English). CODEN: PIXXD2. APPLICATION: WO 1999-US28832 19991206. PRIORITY: US 1998-208541 19981209.
- CVD was used to form a film of Bi oxide, Sr oxide, and Ta oxide on a heated substrate by decompg. the precursors of these oxides at the surface of the substrate. The precursor of Bi oxide is a Bi complex which includes at least one alkoxide group and is decompd. and deposited at a temp. <450.degree.. The film of Bi, Sr, and Ta oxides obtained by low-temp. CVD is predominantly nonferroelec., but can be converted into a ferroelec. film by a subsequent heating process.

IT 7722-84-1, Hydrogen peroxide, uses

10102-43-9, Nitric oxide, uses 10102-44-0, Nitrogen dioxide, uses

(oxidizer; low temp. CVD processes for prepg.

ferroelec. films using bismuth alkoxides)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA
CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N=O

RN 10102-44-0 HCA
CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N=O

RN 1309-48-4 HCA

1344-28-1 HCA

CN Magnesium oxide (MgO) (9CI) (CA INDEX NAME)

Mg = 0

RN

Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) CN*** STRUCTURE DIAGRAM IS NOT AVAILABLE *** ICM C23C016-00 76-8 (Electric Phenomena) CC Section cross-reference(s): 75 7439-88-5, Iridium, uses 7440-05-3, Palladium, uses 7440-16-6, Rhodium, uses 7440-57-5, Gold, uses 12035-99-3, Tungsten oxide IT12036-09-8, Rhenium oxide 12036-02-1, Osmium oxide (OsO2) 12036-10-1, Ruthenium oxide ((ReO2) 12036-22-5, Tungsten oxide (WO2) 12137-15-4, Osmium oxide (OsO) 12137-18-7, Rhodium oxide (RhO) 12137-27-8, Rhodium oxide (RhO2) 12143-03-2, Rhenium oxide (ReO) 12143-05-4, Ruthenium oxide (RuO) 116224-72-7, Bismuth calcium copper strontium oxide (Bi2Ca2Cu3Sr2O10) 117656-29-8, Barium copper ytterbium oxide (Ba2Cu3YbO6-7) 138290-45-6, Titanium 271779-40-9, Zirconium nitride (ZrN0-1) nitride (TiN0-1) 271779-41-0, Tungsten nitride (WN0-1.7) 271779-42-1, Tantalum nitride (TaN0-1.7) (contact; low temp. CVD processes for prepg. ferroelec. films using bismuth alkoxides)

1304-76-3P, Bismuth oxide, processes 1314-11-0P, Strontium oxide, processes 1314-61-0P, Tantalum pentoxide 12010-42-3P, Bismuth iron oxide (BiFeO3) 12010-48-9P, Bismuth niobium potassium oxide (BiNb5K2O15) 12048-25-8P, Bismuth potassium titanium oxide (BiKTi2O6) 12161-72-7P, Barium bismuth vanadium oxide (Ba2BiVO6) 12231-09-3P, Barium bismuth niobium oxide

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12231-10-6P, Barium bismuth tantalum oxide (Ba2BiTaO6)
     (Ba2BiNb06)
    12231-66-2P, Barium bismuth molybdenum oxide (Ba3Bi2MoO9)
    12231-67-3P, Barium bismuth tungsten oxide (Ba3Bi2WO9)
    12232-95-0P, Bismuth manganese oxide (BiMnO3) 12233-01-1P, Bismuth
    lead niobium oxide (BiPb2NbO6) 12233-04-4P, Bismuth lead tantalum
                          12233-27-1P, Bismuth lead molybdenum oxide
    oxide (BiPb2TaO6)
                    13595-86-3P, Bismuth tungsten oxide (Bi2WO6)
     (Bi2Pb3MoO9)
    51403-91-9P, Bismuth niobium strontium oxide (Bi2Nb2SrO9)
    61163-38-0P, Bismuth lead tungsten oxide (Bi2Pb3WO9)
                                                               156832-05-2P,
    Bismuth niobium strontium tantalum oxide (Bi2Nb0-2SrTa0-209)
    167773-21-9P, Bismuth lead vanadium oxide (BiPb2VO6)
                                                               187239-99-2P
                                                    219534-79-9P, Bismuth
                                    219534-66-4P
                    219534-64-2P
    219534-62-0P
     lead molybdenum oxide (BiPb6MoO18) 219534-80-2P, Bismuth lead
     tungsten oxide (BiPb6W018)
        (low temp. CVD processes for prepg. ferroelec. films using
        bismuth alkoxides)
     7722-84-1, Hydrogen peroxide, uses
     10024-97-2, Nitrogen oxide (N2O), uses 10028-15-6, Ozone, uses
     10102-43-9, Nitric oxide, uses
     10102-44-0, Nitrogen dioxide, uses
     12033-49-7, Nitrogen trioxide
        (oxidizer; low temp. CVD processes for prepg.
        ferroelec. films using bismuth alkoxides)
     1303-00-0, Gallium arsenide, uses 1309-48-4, Magnesia,
            1314-23-4, Zirconia, uses 1344-28-1,
                                                  7440-32-6,
                      7440-21-3, Silicon, uses
     Alumina, uses
     Titanium, uses 7631-86-9, Silica, uses
                                                 12033-89-5, Silicon
                      12047-27-7, Barium titanate, uses 12060-00-3, Lead
     nitride, uses
                12060-59-2, Strontium titanate
     titanate
        (substrate; low temp. CVD processes for prepg. ferroelec. films
        using bismuth alkoxides)
     ANSWER 9 OF 21 HCA COPYRIGHT 2003 ACS on STN
132:215653 Fabrication of semiconductor structures and preparation of
     ruthenium oxide films. Vaartstra, Brian
     A.; Marsh, Eugene P. (Micron Technology, Inc., USA). PCT Int. Appl.
     WO 2000012779 A1 20000309, 21 pp. DESIGNATED STATES: W: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE,
     ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP,
     KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ,
     PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM; RW: AT, BE, BF,
     BJ, CF, CG, CH, CI, CM, CY, DE, DK, ES, FI, FR, GA, GB, GR, IE, IT,
     LU, MC, ML, MR, NE, NL, PT, SE, SN, TD, TG. (English). CODEN:
     PIXXD2. APPLICATION: WO 1999-US18193 19990811.
                                                        PRIORITY: US
     1998-140932 19980827.
     The invention provides methods for the prepn. of Ru
     oxide films from liq. Ru complexes of the formula
     (diene) Ru(CO)3, where diene refers to linear, branched, or cyclic
     dienes, bicyclic dienes, tricyclic dienes, their fluorinated
     derivs., their combinations, or derivs. addnl. contg. heteroatoms
     such as halide, Si, S, Se, P, As, N, or O, and an oxidizing gas.
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IT

IT

AB

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Preferred examples are cyclohexadiene- or cycloheptadieneruthenium
     tricarbonyl with O gas.
     7722-84-1, Hydrogen peroxide, processes
IT
     10102-43-9, Nitric oxide, processes 10102-44-0,
     Nitrogen dioxide, processes
        (CVD of ruthenium oxide films from
        ruthenium diene tricarbonyl complexes and)
     7722-84-1 HCA
RN
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
но-он
RN
     10102-43-9 HCA
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
CN
N=== 0
     10102-44-0 HCA
RN
     Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
CN
O- N=O
     ICM C23C016-40
IC
     ICS C01G055-00
     76-3 (Electric Phenomena)
CC
     Section cross-reference(s): 75
     ruthenium oxide film prepn;
ST
     semiconductor structure fabrication; cyclohexadieneruthenium
     tricarbonyl ruthenium oxide film CVD;
     cycloheptadieneruthenium tricarbonyl ruthenium
     oxide film CVD; CVD ruthenium
     oxide film
IT
     Vapor deposition process
         (chem.; CVD of ruthenium oxide films
         for semiconductor structures)
     Semiconductor device fabrication
IT
         (prepn. of ruthenium oxide films
        for semiconductor structures)
                   51403-93-1
     12108-25-7
IT
         (CVD of ruthenium oxide films from)
     7722-84-1, Hydrogen peroxide, processes
IT
     7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes 10102-43-9,
     Nitric oxide, processes 10102-44-0, Nitrogen
     dioxide, processes
         (CVD of ruthenium oxide films from
         ruthenium diene tricarbonyl complexes and)
     11113-84-1P, Ruthenium oxide
IT
         (prepn. of ruthenium oxide films
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for semiconductor structures)

IT 7732-18-5, Water, processes

(vapor; CVD of ruthenium oxide films from ruthenium diene tricarbonyl complexes and)

L53 ANSWER 10 OF 21 HCA COPYRIGHT 2003 ACS on STN

131:38437 Low-temperature CVD of bismuth strontium tantalum oxide films using bismuth amides. Hintermaier, Frank; Van Buskirk, Peter; Roeder, Jeffrey R.; Hendrix, Bryan; Baum, Thomas H.; Desrochers, Debra A. (Siemens Aktiengesellschaft, Germany; Advanced Technology Materials, Inc.). PCT Int. Appl. WO 9929926 A1 19990617, 41 pp. DESIGNATED STATES: W: JP, KR; RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE. (English). CODEN: PIXXD2. APPLICATION: WO 1998-US26257 19981210. PRIORITY: US 1997-69041 19971210.

AB CVD is used to form a film of Bi oxide, Sr oxide, and Ta oxide on a heated substrate by decompg. the precursors of these oxides at the surface of the substrate. The precursor of Bi oxide is a Bi complex which includes .gtoreq.1 amide group and is decompd. and deposited at <450.degree. The film of Bi, Sr, and Ta oxides obtained by low-temp. CVD is predominantly nonferroelec., but can be converted into a ferroelec. film by subsequent heating.

IT 11113-84-1, Ruthenium oxide

(low-temp. CVD of bismuth strontium tantalum oxide ferroelec. films on substrates contg.)

RN 11113-84-1 HCA

CN Ruthenium oxide (9CI) (CA INDEX NAME)

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

IT 7722-84-1, Hydrogen peroxide, processes

10102-43-9, Nitric oxide, processes

10102-44-0, Nitrogen dioxide, processes

(oxidizing agent; in low-temp. CVD of bismuth strontium tantalum oxide films using bismuth amides)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N=== Ο

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N = O

IT 1309-48-4, Magnesium oxide (MgO

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), processes 1344-28-1, Aluminum oxide
     (Al2O3), processes
        (substrate; low-temp. CVD of bismuth strontium tantalum oxide
        films on)
     1309-48-4 HCA
RN
     Magnesium oxide (MgO) (9CI) (CA INDEX NAME)
CN
Mg = 0
     1344-28-1 HCA
RN
     Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME)
CN
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
     ICM C23C016-40
IC
     ICS H01L029-00; C23C018-12; C30B025-02
     76-8 (Electric Phenomena)
CC
     Section cross-reference(s): 75
     1314-35-8, Tungsten oxide (WO3), processes 7439-88-5, Iridium,
IT
                 7440-05-3, Palladium, processes 7440-06-4, Platinum,
     processes 7440-05-3, Palladium, processes 7440-06-4, Pla
processes 7440-16-6, Rhodium, processes 7440-57-5, Gold,
     processes 11113-84-1, Ruthenium oxide
     12624-27-0, Rhenium oxide 12645-46-4, Iridium oxide
                                                               12680-36-3,
                      61970-39-6, Osmium oxide
                                                  110621-08-4, Barium
     Rhodium oxide
     copper yttrium oxide (Ba2Cu3Y06-7)
                                            116224-72-7, Bismuth calcium
                                                  119173-61-4, Zirconium
     copper strontium oxide (Bi2Ca2Cu3Sr2O10)
                138290-45-6, Titanium nitride (TiNO-1) 226225-66-7,
     Tantalum tungsten nitride (TaWN0-2.7)
         (low-temp. CVD of bismuth strontium tantalum oxide ferroelec.
        films on substrates contg.)
     7722-84-1, Hydrogen peroxide, processes
IT
     7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes 10102-43-9,
     Nitric oxide, processes 10102-44-0,
                                     12033-49-7, Nitrogen
     Nitrogen dioxide, processes
     oxide (NO3)
         (oxidizing agent; in low-temp. CVD of bismuth strontium
         tantalum oxide films using bismuth amides)
     1303-00-0, Gallium arsenide, processes 1309-48-4,
IT
     Magnesium oxide (MgO), processes
     1314-23-4, Zirconium oxide (ZrO2), processes 1344-28-1,
     Aluminum oxide (Al2O3), processes
                                      7631-86-9, Silica, processes
     7440-21-3, Silicon, processes
     12033-89-5, Silicon nitride (Si3N4), processes 12047-27-7, Barium
     titanate (BaTiO3), processes 12060-00-3, Lead titanium oxide
                 12060-59-2, Strontium titanate (SrTiO3)
         (substrate; low-temp. CVD of bismuth strontium tantalum oxide
         films on)
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L53 ANSWER 11 OF 21 HCA COPYRIGHT 2003 ACS on STN
131:26686 Low-temperature CVD of bismuth strontium tantalum oxide films
using bismuth carboxylates. Hintermaier, Frank; Van Buskirk, Peter;
Roeder, Jeffrey R.; Hendrix, Bryan; Baum, Thomas H.; Desrochers,

Debra A. (Siemens Aktiengesellschaft, Germany; Advanced Technology Materials, Inc.). PCT Int. Appl. WO 9929925 A1 19990617, 38 pp. DESIGNATED STATES: W: JP, KR; RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE. (English). CODEN: PIXXD2. APPLICATION: WO 1998-US26256 19981210. PRIORITY: US 1997-69058 19971210. CVD is used to form a film of Bi oxide, Sr oxide, and Ta oxide on a heated substrate by decompg. the precursors of these oxides at the surface of the substrate. The precursor of Bi oxide is a Bi complex which includes .gtoreq.1 carboxylate group and is decompd. and deposited at <450.degree.. The film of Bi, Sr, and Ta oxides obtained by low-temp. CVD is predominantly nonferroelec., but can be converted into a ferroelec. film by subsequent heating. 11113-84-1, Ruthenium oxide (low-temp. CVD of bismuth strontium tantalum oxide ferroelec. films on substrates contg.) 11113-84-1 HCA Ruthenium oxide (9CI) (CA INDEX NAME) *** STRUCTURE DIAGRAM IS NOT AVAILABLE *** 7722-84-1, Hydrogen peroxide, processes 10102-43-9, Nitric oxide, processes 10102-44-0, Nitrogen dioxide, processes (oxidizing agent; in low-temp. CVD of bismuth strontium tantalum oxide films using bismuth carboxylates) 7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) HO-OH 10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) N = 010102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) O- N= O 1309-48-4, Magnesium oxide (MgO), processes 1344-28-1, Aluminum oxide (Al2O3), processes

(substrate; low-temp. CVD of bismuth strontium tantalum oxide

Mq = 0

films on)

HCA

Magnesium oxide (MgO) (9CI) (CA INDEX NAME)

1309-48-4

AΒ

IT

RN

CN

IT

RN

CN

RN

CN

RN

CN

IT

RN

CN

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1344-28-1 HCA
RN
     Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME)
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
     ICM C23C016-40
     ICS H01L029-00; C23C018-12; C30B025-02
     76-8 (Electric Phenomena)
     Section cross-reference(s): 75
     1314-35-8, Tungsten oxide (WO3), processes 7439-88-5, Iridium,
IT
                 7440-05-3, Palladium, processes 7440-06-4, Platinum,
     processes 7440-05-3, Palladium, processes processes 7440-16-6, Rhodium, processes
                                                7440-57-5, Gold,
     processes 11113-84-1, Ruthenium oxide
     12624-27-0, Rhenium oxide 12645-46-4, Iridium oxide
                                                              12680-36-3,
                                                110621-08-4, Barium
                     61970-39-6, Osmium oxide
     Rhodium oxide
                                          116224-72-7, Bismuth calcium
     copper yttrium oxide (Ba2Cu3YO6-7)
     copper strontium oxide (Bi2Ca2Cu3Sr2O10) 119173-61-4, Zirconium
               138290-45-6, Titanium nitride (TiNO-1)
                                                        226225-66-7,
     Tantalum tungsten nitride (TaWN0-2.7)
        (low-temp. CVD of bismuth strontium tantalum oxide ferroelec.
        films on substrates contg.)
     7722-84-1, Hydrogen peroxide, processes
_{
m IT}
     7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O),
                 10028-15-6, Ozone, processes 10102-43-9,
     processes
     Nitric oxide, processes 10102-44-0,
                                    12033-49-7, Nitrogen
     Nitrogen dioxide, processes
     oxide (NO3)
         (oxidizing agent; in low-temp. CVD of bismuth strontium
        tantalum oxide films using bismuth carboxylates)
     1303-00-0, Gallium arsenide, processes 1309-48-4,
IT
     Magnesium oxide (MgO), processes
     1314-23-4, Zirconium oxide (ZrO2), processes 1344-28-1,
     Aluminum oxide (Al2O3), processes
                                     7631-86-9, Silica, processes
     7440-21-3, Silicon, processes
     12033-89-5, Silicon nitride (Si3N4), processes 12047-27-7, Barium
     titanate (BaTiO3), processes 12060-00-3, Lead titanium oxide
                 12060-59-2, Strontium titanate (SrTiO3)
      (PbTiO3)
         (substrate; low-temp. CVD of bismuth strontium tantalum oxide
         films on)
     ANSWER 12 OF 21 HCA COPYRIGHT 2003 ACS on STN
124:184167 Control of nitrogen oxide emissions by hydrogen
     peroxide-enhanced gas-phase oxidation of
     nitric oxide. Kasper, John M.; Clausen, Christian
     A. III; Cooper, C. David (University of Central Florida, Orlando,
     FL, USA). Journal of the Air & Waste Management Association, 46(2),
     127-33 (English) 1996. CODEN: JAWAFC. Publisher: Air & Waste
     Management Association.
     NOx and SOx are criteria air pollutants, emitted in large quantities
AB
     from fossil-fueled elec. power plants. Emissions of SOx are
     currently being reduced significantly in many places by wet
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scrubbing of the exhaust or flue gases, but most of the NOx in the flue gases is NO, which is so insol. that it is virtually impossible

to scrub. Consequently, NOx control is mostly achieved using combustion modifications to limit the formation of NOx, or by using chem. redn. techniques to reduce NOx to N. Low NOx burners are relatively inexpensive but can only achieve .apprx.50% redn. in NOx emissions; selective catalytic redn. (SCR) can achieve high redns. but is very expensive. The removal of NOx in wet scrubbers could be greatly enhanced by gas-phase oxidn. of the NO to NO2, HNO2, and HNO3 (the acid gases are much more sol. in water than NO). This oxidn. is accomplished by injecting liq. H2O2 into the flue gas; the H2O2 vaporizes and dissocs. into hydroxyl radicals. The active OH radicals then oxidize the NO and NO2. This NOx control technique might prove economically feasible at power plants with existing SO2 scrubbers. The higher chem. costs for H202 would be balanced by the investment cost savings, compared with an alternative such as SCR. The oxidn. of NOx by H2O2 was demonstrated in a lab. quartz tube reactor. NO conversions of 97 and 75% were achieved at H2O2/NO mole ratios of 2.6 and 1.6, resp. The reactor conditions (500.degree., a pressure of one atm., and 0.7 s residence time) are representative of flue gas conditions for a variety of The oxidized NOx species were removed by combustion sources. caustic water scrubbing.

7722-84-1, Hydrogen peroxide, uses
(control of nitrogen oxide emissions by hydrogen
peroxide-enhanced gas-phase oxidn. of
nitric oxide)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

но-он

CC 59-4 (Air Pollution and Industrial Hygiene) Section cross-reference(s): 51

ST nitrogen oxide oxidn hydrogen peroxide

IT Scrubbers

(wet, control of nitrogen oxide emissions by hydrogen peroxide-enhanced gas-phase oxidn. of nitric oxide)

IT 10102-43-9, Nitric oxide, processes 11104-93-1, Nitrogen oxide, processes

(control of nitrogen oxide emissions by hydrogen peroxide-enhanced gas-phase oxidn. of nitric oxide)

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ANSWER 13 OF 21 HCA COPYRIGHT 2003 ACS on STN
L53
           Catalytic oxidation for removal of nitrogen oxides from waste
     gases using hydrogen peroxide. von Wedel,
     Wedigo; Barenschee, Ernst Robert; Eickhoff, Hubertus (Degussa A.-G.,
    Germany). Ger. DE 4136183 C1 19930408, 11 pp. (German). CODEN:
     GWXXAW. APPLICATION: DE 1991-4136183 19911102.
     Waste gases, e.g., flue gases and incinerator waste gases, are
AΒ
     treated at <180.degree., preferably 20-100.degree., with
    H2O2 using a finely divided, granular, prilled, or honeycomb
     catalyst of silica gel, zeolites, porous ion exchangers,
     phyllosilicates, diatomaceous earth, alumina, titania, layered
     silicates, or activated carbon catalyst. The product gases are used
     to produce HNO3 or a NO3- soln., which can be used to scrub the
     gases, enriching the gases to a recoverable product. Alkali or alk.
     earth metal hydroxide soln. can be used in the scrubbing soln. to
     control product recovery.
     10102-43-9, Nitrogen oxide (NO), miscellaneous
IT
     10102-44-0, Nitrogen oxide (NO2), miscellaneous
        (pollutant, in catalytic oxidn. for removal of nitrogen oxides
        from waste gases using hydrogen peroxide)
     10102-43-9 HCA
RN
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
CN
N = 0
     10102-44-0 HCA
RN
     Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
CN
O - N = O
     7722-84-1, Hydrogen peroxide,
IT
     miscellaneous
        (reactant, in catalytic oxidn. for removal of nitrogen oxides
        from waste gases using hydrogen peroxide)
     7722-84-1
RN
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
HO-OH
TC
     ICM B01D053-36
          C01B021-38; G05D021-02
     ICS
     B01J021-08; B01J029-04; B01J031-08; B01J021-04; B01J021-06;
ICA
     B01J021-16; B01J021-18
     59-4 (Air Pollution and Industrial Hygiene)
CC
IT
     Ion exchangers
         (catalyst, in catalytic oxidn. for removal of nitrogen oxides
         from waste gases using hydrogen peroxide)
     Kieselguhr
IT
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Silica gel, uses Zeolites, uses (catalyst, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) Recycling TT(catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide for) IT Flue gases Waste gases (catalytic oxidn. for removal of nitrogen oxides from, using hydrogen peroxide) Oxidation catalysts IT (for removal of nitrogen oxides from waste gases using hydrogen peroxide) Alkali metal hydroxides ΙT Alkali metals, uses Alkaline earth hydroxides Alkaline earth metals (in catalytic oxidn. for removal of nitrogen oxides from waste qases using hydrogen peroxide) Nitrates, preparation IT (product, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) ITSilicates, uses (layered, catalyst, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) Silicates, uses IT(phyllo-, catalyst, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide Minerals IT(phyllosilicate, catalyst, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) 7440-44-0, Carbon, miscellaneous IT (activated, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) 1344-28-1, Alumina, uses 12173-98-7, Mordenite 13463-67-7, ITTitania, uses (catalyst, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide) 10102-43-9, Nitrogen oxide (NO), miscellaneous IT10102-44-0, Nitrogen oxide (NO2), miscellaneous 11104-93-1, Nitrogen oxide, miscellaneous (pollutant, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide)

miscellaneous
(product, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide)
7722-84-1, Hydrogen peroxide,

7697-37-2, Nitric acid, miscellaneous

IT

ΙT

14797-55-8, Nitrate,

miscellaneous

(reactant, in catalytic oxidn. for removal of nitrogen oxides from waste gases using hydrogen peroxide)

- L53 ANSWER 14 OF 21 HCA COPYRIGHT 2003 ACS on STN
- 118:65829 Air contaminants. (Occupational Safety and Health Administration, U. S. Dep. Labor, Washington, DC, 20210, USA). Federal Register, 57(114, Bk. 2), 26002-601 (English) 12 Jun 1992. CODEN: FEREAC. ISSN: 0097-6326.
- Proposed amendments of existing air contaminant stds. for the AB maritime and construction industries and extension of air contaminant stds. to agricultural employees (only employees of farms with >10 nonfamily employees are covered) are given under the Federal Occupational Safety and Health Administration. Tables that indicated transitional limits, based on established threshold limit values, indication of skin protection needs, proposed time-weighted av. exposure (any 8-h work shift for 40-h week), short-term exposure limit (15-min time-weighted av.), ceiling (exposure during any part of the work day, or if instantaneous monitoring is not feasible, the 15-min time-weighted av.), and/or skin protection needs are given for the shipyard, marine terminal and longshoring, construction, and agricultural industries. Extensive data on health effects of the substances to be regulated and preliminary regulatory impact analyses are given for general industry and the specific industrial sectors.
- TT 7722-84-1, Hydrogen peroxide, biological studies 10102-43-9, Nitric oxide, biological studies 10102-44-0, Nitrogen dioxide, biological studies

(exposure limits to airborne, in agricultural and construction and maritime industries, stds. for)

- L53 ANSWER 15 OF 21 HCA COPYRIGHT 2003 ACS on STN
- 116:27324 Removal of acids and heavy metals from liquids by neutralization. Boguslawski, Zbigniew (Aquamot A.-G., Switz.). Ger. Offen. DE 4010321 Al 19911002, 14 pp. (German). CODEN: GWXXBX. APPLICATION: DE 1990-4010321 19900330.
- AB Acids and heavy metals are removed from wastewaters and acid condensates from heating plants by neutralization using pelletized bases, e.g. Mg(OH)2, after passage through a layer of bentonite pellets. The treated effluent is then passed through a layer of Fe(OH)3 pellets. The system effectively removes SO2, SO3, NOx, hydrocarbons, and halohydrocarbons and partially oxidizes NO and CO.
- TT 7722-84-1, Hydrogen peroxide, uses
 (in removal of heavy metals and acids from wastewaters by
 neutralization with manganese hydroxide)
- RN 7722-84-1 HCA
- CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

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RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N=O

IC ICM C02F001-66 ICS C02F001-62; B01D053-34; B01D053-18; F23J015-00; B01J020-16

ICA C01F011-02; C01B033-21; C01G045-02

CC 60-2 (Waste Treatment and Disposal)

magnesium hydroxide)

IT 3811-04-9, Potassium chlorate 7722-84-1, Hydrogen peroxide, uses

(in removal of heavy metals and acids from wastewaters by neutralization with manganese hydroxide)

- IT 630-08-0, Carbon monoxide, miscellaneous 2382-64-1 7439-92-1, Lead, miscellaneous 7439-97-6, Mercury, miscellaneous 7440-43-9, Cadmium, miscellaneous 7440-47-3, Chromium, miscellaneous 7440-66-6, Zinc, miscellaneous 7446-09-5, Sulfur dioxide, miscellaneous 7446-11-9, Sulfur trioxide, miscellaneous 10102-43-9, Nitric oxide, miscellaneous 10102-44-0, Nitrogen dioxide, miscellaneous 11104-93-1, Nitrogen oxide, miscellaneous 20427-58-1, Zinc hydroxide (removal of, from wastewaters by neutralization using pelletized
- L53 ANSWER 16 OF 21 HCA COPYRIGHT 2003 ACS on STN 106.72244 Method and apparatus for removing exides of
- 106:72244 Method and apparatus for removing oxides of nitrogen and sulfur from combustion gases. Jones, Gordon Dale (USA). PCT Int. Appl. WO 8606711 A1 19861120, 107 pp. DESIGNATED STATES: W: AT, AU, BR, CH, DE, DK, FI, GB, HU, JP, KP, LK, LU, MC, MG, MW, NL, NO, RO, SE, SU; RW: AT, BE, CH, DE, FR, GB, IT, LU, NL, SE. (English). CODEN: PIXXD2. APPLICATION: WO 1985-US1022 19850603. PRIORITY: US 1985-734393 19850514.
- AB NO is converted to NO2 by contacting the NO-contg. gas, e.g., at .gtorsim.800.degree.F, with an injection gas contg. a peroxyl initiator, e.g., C3H8, MeOH, or H2O2, and sufficient O for the conversion, e.g., .apprx.5 .simeq. 20%. The process may be the first step in the removal of NOx and SOx from

flue gases; the gas stream leaves the conversion zone with a NO-NO2 molar ratio of .ltorsim.2:1 and enters an absorption zone where it contacts a particulate absorbent, e.g., NaHCO3 and/or Na2CO3 or Ca(OH)2, for NOx and SOx. The particulate matter may then be removed from the gas stream e.g., with a baghouse filter, and then the gas may be contacted with a metal oxide, e.g., Al203, to adsorb residual NOx. Many variations of the method are also claimed along with an app. including a NO conversion section and an absorption section. Thus, when .apprx.2480 ppm C3H8 was injected into a flue gas contg. NO, with simultaneous injection of air at 6.2 ft3/h providing 3.7% excess 0, 55% of the NO was converted to NOx at gas temp. 1350.degree.F. The flue gas with decreased NO concn. and increased NO2 concn. was then treated in a scrubbing section with dry particulate Trona or Nahcolite to remove SO2, NO2, and residual NO. 10102-44-0P, Nitrogen dioxide, uses and miscellaneous (formation and removal of, in flue gas treatment) 10102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) O- N= O 1309-48-4, Magnesia, biological studies 1332-37-2, biological studies 1344-28-1, Alumina, biological studies (in dry scrubbing of flue gases, for residual nitrogen oxide removal, after oxidn. and scrubbing) 1309-48-4 HCA Magnesium oxide (MgO) (9CI) (CA INDEX NAME) Mq = 01332-37-2 HCA Iron oxide (8CI, 9CI) (CA INDEX NAME) *** STRUCTURE DIAGRAM IS NOT AVAILABLE *** 1344-28-1 HCA Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) *** STRUCTURE DIAGRAM IS NOT AVAILABLE *** 7722-84-1, Hydrogen peroxide, reactions (peroxyl initiator, in oxidn. of nitric oxide in flue gases) 7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

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IC ICM C01B021-00 ICS C01B021-22

- 59-4 (Air Pollution and Industrial Hygiene) CC nitric oxide oxidn flue gas; peroxyl STinitiator oxidn nitric oxide; scrubbing flue gas desulfurization denitration IT Absorbents (liq. and particulate, in scrubbing of flue gases with prior nitric oxide oxidn.) IT (nitrogen oxide and sulfur oxide removal from, nitric oxide oxidn. and scrubbing for) IT Scrubbing (of flue gases, dry and/or wet, with prior nitric oxide oxidn.) Alcohols, uses and miscellaneous IT (peroxyl initiator, in oxidn. of nitric oxide in flue gases) 10102-44-0P, Nitrogen dioxide, uses and IT miscellaneous (formation and removal of, in flue gas treatment) 144-55-8, Sodium bicarbonate, biological studies 497-19-8, Sodium IT biological studies
- carbonate, biological studies 1305-62-0, Calcium hydroxide, (in dry or wet scrubbing of flue gases, with prior nitric oxide oxidn.) 1309-48-4, Magnesia, biological studies 1314-23-4, IT
- Zirconia, biological studies 1332-37-2, biological studies 1344-28-1, Alumina, biological studies 1344-70-3, Copper oxide 12057-24-8, Lithium oxide, biological 13463-67-7, Titania, biological studies Nickel oxide

(in dry scrubbing of flue gases, for residual nitrogen oxide removal, after oxidn. and scrubbing)

60-00-4, EDTA, biological studies 7439-89-6D, Iron, complexes IT 7720-78-7, Ferrous sulfate (in wet scrubbing of flue gases, with prior nitric oxide oxidn.)

67-56-1, Methanol, reactions 74-98-6, Propane, reactions IT1333-74-0, Hydrogen, reactions 7722-84-1, Hydrogen peroxide, reactions (peroxyl initiator, in oxidn. of nitric oxide in flue gases)

IT (removal of nitrogen oxides and, from flue gases, nitric oxide oxidn. and scrubbing for)

11104-93-1, uses and miscellaneous IT(removal of sulfur oxides and, from flue gases, nitric oxide oxidn. and scrubbing for)

10102-43-9, Nitric oxide, uses and miscellaneous IT(removal of, from flue gases, conversion to nitrogen dioxide in, app. and method for)

ANSWER 17 OF 21 HCA COPYRIGHT 2003 ACS on STN L53

- 105:84364 Mathematical modeling of chemically reactive pollutants in indoor air. Nazaroff, William W.; Cass, Glen R. (Environ. Eng. Sci., California Inst. Technol., Pasadena, CA, 91125, USA). Environmental Science and Technology, 20(9), 924-34 (English) 1986. CODEN: ESTHAG. ISSN: 0013-936X.
- AB A general math. model is presented for predicting the concns. of chem. reactive compds. in indoor air. The model accounts for the effects of ventilation, filtration, heterogeneous removal, direct emission, and photolytic and thermal chem. reactions. The model is applied to the induction of photochem. reactive pollutants into a museum gallery, and the predicted NO, NOx-NO, and O3 concns. are compared to measured data. The model predicts substantial prodn. of several species due to chem. reaction, including HNO2, HNO3, NO3, and N2O5. Circumstances in which homogeneous chem. may assume particular importance are identified and include buildings with glass walls, indoor combustion sources, and direct emission of olefins.

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O- N-O

- CC 59-2 (Air Pollution and Industrial Hygiene)
- TT 50-00-0, biological studies 2278-22-0 3170-83-0 3352-57-6, biological studies 7697-37-2, biological studies 7722-84-1, biological studies 7782-77-6 10028-15-6, biological studies 10102-03-1 10102-43-9, biological studies 10102-44-0, biological studies 12033-49-7 26404-66-0

- L53 ANSWER 18 OF 21 HCA COPYRIGHT 2003 ACS on STN 97:60267 Removal of nitrogen oxide from flue gases. (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 57027118 A2 19820213 Showa, 3 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1980-101328 19800725.
- AB NO is removed from flue gases by catalytic oxidn.-redn. with

H2O2 and NH3, resp. Thus, flue gas contg. 110 ppm NO and 8
vol.% O was mixed with 1.1 and 1.2 equiv. amts. (based on the NO) of
NH3 and H2O2, and the mixt. was passed through a V2O5Al2O3 redox catalyst at 400.degree. to achieve a >95%
NO-removal efficiency.

IT **7722-84-1**, reactions

(nitric oxide oxidn. by, prior to redn. with ammonia, in flue gas treatment)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

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IC B01D053-36

CC 59-4 (Air Pollution and Industrial Hygiene)

ST nitric oxide removal flue gas; vanadium oxide redox catalyst; hydrogen peroxide flue gas redn; ammonia flue gas redn

IT Flue gases

(nitric oxide removal from, by catalytic oxidn.-redn. with ammonia and hydrogen peroxide)

IT Redox reaction catalysts

(vanadium oxide-alumina, for nitric oxide removal from flue gas with hydrogen peroxide and ammonia)

IT **7722-84-1**, reactions

(nitric oxide oxidn. by, prior to redn. with ammonia, in flue gas treatment)

IT 7664-41-7, reactions

(redn. by, of **nitrogen dioxide**, in flue gas denitration)

IT 1314-62-1, uses and miscellaneous

(redox catalyst, for nitric oxide removal from flue gas with hydrogen peroxide and ammonia)

IT 10102-43-9, uses and miscellaneous

(removal of, from flue gas, by oxidn.-redn. with hydrogen peroxide and ammonia, redox catalyst for)

L53 ANSWER 19 OF 21 HCA COPYRIGHT 2003 ACS on STN

- 96:96706 Analysis of the composition of a gaseous mixture containing nitric oxide and nitrogen peroxide. Alvarez Gonžalez, J. R.; Fernandez Tena, A.; Lara Olivares, A. (Fac. Cienc., Univ. Salamanca, Salamanca, Spain). Afinidad, 38(375), 418-21 (Spanish) 1981. CODEN: AFINAE. ISSN: 0001-9704.
- NO, NO2, and N204 are detd. simultaneously, as NO and NO2, by H2O2 consumption and HNO3 formation. (The equil. mixt. of NO2 and N2O4 is here termed N peroxide.).

 A glass flask with a capillary stopcock, contg. H2O, is evacuated, flushed with N, and filled with the gaseous mixt. contg. x mol NO and y mol NO2. A known excess of H2O2 is added through the stopcock; after shaking for 15-20 min, the HNO3 formed is titrated with NaOH. After acidifying, excess H2O2

is titrated with KMnO4. The compn. of the mixt. is calcd. from x +y = moles HNO3, and 1.5x + 0.5y = moles H2O2 consumed. The error in all cases was <4%. 10102-43-9, analysis IT (detn. of, in mixt. with nitrogen dioxide by reaction with hydrogen peroxide and titrimetry) 10102-43-9 HCA RNNitrogen oxide (NO) (8CI; 9CI) (CA INDEX NAME) CN N = 0IT 10102-44-0, analysis (detn. of, in mixts. with nitric oxide by reaction with hydrogen peroxide and titrimetry) 10102-44-0 HCA RNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN O-N==O79-6 (Inorganic Analytical Chemistry) CCnitric oxide detn gas mixt; nitrogen dioxide ST detn gas mixt; oxide nitrogen detn gas mixt; gas mixt analysis nitrogen oxide; titrimetry analysis nitrogen oxide mixt 10102-43-9, analysis IT (detn. of, in mixt. with nitrogen dioxide by reaction with hydrogen peroxide and titrimetry) 10102-44-0, analysis IT (detn. of, in mixts. with nitric oxide by reaction with hydrogen peroxide and titrimetry) ANSWER 20 OF 21 HCA COPYRIGHT 2003 ACS on STN 92:168156 Comparison of stack sampling methods for nitrogen oxides. James, Robert E.; Cunningham, James E. (Texas Air Control Board, Austin, TX, USA). Proceedings, Annual Meeting - Air Pollution Control Association, 71st. Vol. 3, Paper 78-35.6, 15 pp. (English) CODEN: PRAPAP. ISSN: 0099-4081. In a simplified method for sampling NOx emissions, stack gas is AB collected in a volumetrically calibrated 0.5-1.2 L glass flow-through bomb. NO and NO2 are converted to NO3- by aq. H2O2, which is injected immediately after sample collection. NO3- is detd. by the PhOH/disulfonic acid method. Field testing at 4 fossil fuel-fired boilers showed that the precision and accuracy of the method equal or exceed those of the US

Environmental Protection Agencys ref. method. The app. can be

transported and the sampling performed by an individual, instead of the team needed for the ref. method. The method can also be used to

sample NO calibration std. gas cylinders. IT 10102-43-9, analysis

(sampling of, from calibration gas cylinders)
RN 10102-43-9 HCA
CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N=0

CC 59-1 (Air Pollution and Industrial Hygiene)

CC 59-1 (Air Pollution and Industrial Hygiene)
Section cross-reference(s): 79

IT 10102-43-9, analysis
(sampling of, from calibration gas cylinders)

L53 ANSWER 21 OF 21 HCA COPYRIGHT 2003 ACS on STN

85:24928 Dosimeter for oxides of nitrogen. Ferber, B. I.; Sharp,
Frederick A.; Freedman, Robert W. (Pittsburgh Min. Saf. Res. Cent.,
Bur. Mines, Pittsburgh, PA, USA). American Industrial Hygiene
Association Journal (1958-1999), 37(1), 32-6 (English) 1976. CODEN:
ATHAAP. ISSN: 0002-8894.

The personal dosimeter consists of a glass filter impregnated with Na2Cr2O7 and H2SO4, for oxidizing NO to NO2, an unbacked dimethyl silicone membrane, that is permeable to NO2, and a chamber contg. an absorbing soln. (H2SO4 0.0005 and H2O2 0.004M) that oxidizes the NO2 to NO3-. The NO3- is detd. by a specific ion electrode. The measurement precision is good. The oxidizing filter is not used if only NO2 monitoring is desired.

IT 10102-43-9, analysis 10102-44-0, analysis (detn. of, in air, dosimeter for)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = O

RN 10102-44-0 HCA CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N=O

CC 59-1 (Air Pollution and Industrial Hygiene)
Section cross-reference(s): 49

10102-43-9, analysis 10102-44-0, analysis
(detn. of, in air, dosimeter for)

=> d 154 1-13 cbib abs hitstr hitind

L54 ANSWER 1 OF 13 HCA COPYRIGHT 2003 ACS on STN
138:155822 Process for separation of NOx from N2O in a mixture. Chiang,
Chen-chou; Vo, Toan P. (Calgon Carbon Corporation, USA). U.S. US
6517797 B1 20030211, 5 pp. (English). CODEN: USXXAM. APPLICATION:

US 1997-806912 19970226.

The present invention is a reactive adsorption process for sepg. NOx (NO and NO2/N2O4) from N2O in a mixt. The process comprises (A) selectively converting NO to NO2/N2O4 in a mixt. with an oxidant and (B) selectively adsorbing NO2/N2O4 from the mixt. by an adsorbent and .COPYRGT. recovering a stream of N2O having a substantially reduced NOx concn. The adsorbed NOx can be recovered from the adsorbent by elevated temp., reduced pressure, inert gas purge, water wash or any combination thereof.

IT 1344-28-1, Alumina, uses

(activated; process for sepn. of NOx from N2O in a mixt. by adsorption)

RN 1344-28-1 HCA

CN Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME)

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

TT 7722-84-1, Hydrogen peroxide, reactions (oxidizing agent; process for sepn. of NOx from N2O in a mixt. by adsorption)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

IT 1332-37-2, Iron oxide, uses (process for sepn. of NOx from N2O in a mixt. by adsorption)

RN 1332-37-2 HCA

CN Iron oxide (8CI, 9CI) (CA INDEX NAME)

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

IT 10102-44-0, Nitrogen dioxide, processes (process for sepn. of NOx from N2O in a mixt. by adsorption)

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

0-N=0

IT 10102-43-9, Nitric oxide, reactions (process for sepn. of NOx from N2O in a mixt. by adsorption)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

IC ICM C01B021-22 ICS B01D053-04

NCL 423400000; 095129000; 423239100; 423402000

CC 49-3 (Industrial Inorganic Chemicals)

IT 1344-28-1, Alumina, uses (activated; process for sepn. of NOx from N2O in a mixt. by

adsorption)

IT 7722-64-7, Potassium permanganate 7722-84-1,

Hydrogen peroxide, reactions 7782-44-7, Oxygen,

reactions 10028-15-6, Ozone, reactions

(oxidizing agent; process for sepn. of NOx from N2O in a mixt. by adsorption)

IT 1313-99-1, Nickel oxide, uses 1332-37-2, Iron

oxide, uses 1335-30-4, Aluminum silicate 1344-70-3,

Copper oxide (CuOx) 11104-61-3, Cobalt oxide 11129-60-5, Manganese oxide (MnOx) 12656-44-9, Aluminum carbon oxide

(process for sepn. of NOx from N2O in a mixt. by adsorption)

IT 10102-44-0, Nitrogen dioxide, processes

10544-72-6, Nitrogen oxide (N2O4)

(process for sepn. of NOx from N2O in a mixt. by adsorption)

IT 10102-43-9, Nitric oxide, reactions

(process for sepn. of NOx from N2O in a mixt. by adsorption)

L54 ANSWER 2 OF 13 HCA COPYRIGHT 2003 ACS on STN

- 138:65146 Low temperature CVD processes for preparing oxide ferroelectric films using metal alkoxides. Hintermaier, Frank S.; Van Buskirk, Peter C.; Roeder, Jeffrey F.; Hendrix, Bryan C.; Baum, Thomas H.; Desrochers, Debra A. (Advanced Technology Materials, Inc., USA; Infineon Technologies Corporation). U.S. US 6500489 B1 20021231, 18 pp., Cont.-in-part of U.S. 6,303,391. (English). CODEN: USXXAM. APPLICATION: US 1998-208541 19981209. PRIORITY: US 1996-758599 19961127; US 1997-975087 19971120.
- AB CVD is used to form a film of Bi oxide, Sr oxide, and Ta oxide on a heated substrate by decompg. the precursors of these oxides at the surface of the substrate. The precursor of Bi oxide is a Bi complex which includes at least one alkoxide group and is decompd. and deposited at a temp. <450.degree.. The film of Bi, Sr, and Ta oxides obtained by low-temp. CVD is predominantly nonferroelec., but can be converted into a ferroelec. film by a subsequent heating process.

TT 7722-84-1, Hydrogen peroxide, processes

10102-43-9, Nitrogen oxide (NO), processes

10102-44-0, Nitrogen dioxide, processes

(oxidizer; low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO—OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CNO-N = O1309-48-4, Magnesium oxide (MgO IT), processes 1344-28-1, Aluminum oxide (Al2O3), processes (substrate; low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides) 1309-48-4 HCA RNMagnesium oxide (MgO) (9CI) (CA INDEX NAME) CNMq = 01344-28-1 HCA RN Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) CNSTRUCTURE DIAGRAM IS NOT AVAILABLE *** *** ICM C23C016-40 IC427255310; 427255320; 427314000; 427372200 NCL CC76-8 (Electric Phenomena) Section cross-reference(s): 75 7440-04-2, Osmium, uses 7440-05-3, 7439-88-5, Iridium, uses ITPalladium, uses 7440-06-4, Platinum, uses 7440-15-5, Rhenium, 7440-18-8, Ruthenium, uses 7440-16-6, Rhodium, uses 7440-57-5, Gold, uses 12030-48-7, Iridium oxide (IrO) 12030-49-8, Iridium oxide (IrO2) 12035-99-3, Tungsten oxide (WO) 12036-09-8, Rhenium oxide (ReO2) 12036-02-1, Osmium oxide (OsO2) 12036-10-1, Ruthenium oxide (RuO2) 12036-22-5, Tungsten oxide (WO2) 12137-18-7, Rhodium oxide (RhO) 12137-27-8, Rhodium oxide (RhO2) 12143-03-2, Rhenium oxide (ReO) 12143-05-4, Ruthenium oxide (RuO) 116224-72-7, Bismuth calcium copper strontium oxide (Bi2Ca2Cu3Sr2O10) 117656-29-8, Barium copper ytterbium oxide (Ba2Cu3YbO6-7) 138290-45-6, Titanium nitride (TiNO-1) 271779-40-9, Zirconium 271779-41-0, Tungsten nitride (WN0-1.7) nitride (ZrN0-1) 271779-42-1, Tantalum nitride (TaN0-1.7) (electrode; low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides) 1304-76-3, Bismuth oxide, processes 1314-11-0, Strontium oxide, IT1314-61-0, Tantalum oxide 12010-42-3, Bismuth iron oxide (BiFeO3) 12010-48-9, Bismuth niobium potassium oxide (BiNb5K2O15) 12048-25-8, Bismuth potassium 12161-72-7, Barium bismuth vanadium titanium oxide (BiKTi2O6) 12231-09-3, Barium bismuth niobium oxide oxide (Ba2BiVO6) 12231-10-6, Barium bismuth tantalum oxide (Ba2BiTaO6) (Ba2BiNbO6) 12231-66-2, Barium bismuth molybdenum oxide (Ba3Bi2MoO9) 12231-67-3, Barium bismuth tungsten oxide (Ba3Bi2WO9) 12232-95-0, Bismuth manganese oxide (BiMnO3) 12233-01-1, Bismuth lead niobium 12233-04-4, Bismuth lead tantalum oxide oxide (BiPb2Nb06) (BiPb2TaO6) 12233-27-1, Bismuth lead molybdenum oxide (Bi2Pb3MoO9) 13595-86-3, Bismuth tungsten oxide (Bi2WO6) 50811-07-9, Bismuth strontium tantalum oxide (Bi2SrTa2O9) 61163-38-0, Bismuth lead tungsten oxide (Bi2Pb3WO9) 167773-21-9, Bismuth lead vanadium oxide (BiPb2VO6) 187239-99-2 188359-86-6, Bismuth niobium strontium tantalum oxide 219534-62-0 219534-64-2 219534-66-4 219534-76-6, Barium bismuth molybdenum oxide (Ba6BiMoO18) 219534-78-8, Barium bismuth tungsten oxide (Ba6BiWO18) 219534-79-9, Bismuth lead molybdenum oxide (BiPb6MoO18) 219534-80-2, Bismuth lead tungsten oxide (BiPb6WO18) (low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides) 7722-84-1, Hydrogen peroxide, processes

7722-84-1, Hydrogen peroxide, processes
7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O),
processes 10028-15-6, Ozone, processes 10102-43-9,
Nitrogen oxide (NO), processes 10102-44-0,
Nitrogen dioxide, processes 12033-49-7, Nitrogen
trioxide

(oxidizer; low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides)

1303-00-0, Gallium arsenide (GaAs), processes 1309-48-4, Magnesium oxide (MgO), processes 1314-23-4, Zirconium oxide (ZrO2), processes 1344-28-1, Aluminum oxide (Al2O3), processes

7631-86-9, Silicon oxide (SiO2), processes 12033-89-5, Silicon nitride (Si3N4), processes 12047-27-7, Barium titanium oxide (BaTiO3), processes 12060-00-3, Lead titanium oxide (PbTiO3) 12060-59-2, Strontium titanium oxide (SrTiO3)

(substrate; low temp. CVD processes for prepg. oxide ferroelec. films using metal alkoxides)

L54 ANSWER 3 OF 13 HCA COPYRIGHT 2003 ACS on STN

- 137:267469 Populations at risk. Pedersen, David H.; Young, Randy O.; Rose, Vernon E. (National Institute for Occupational Safety and Health, Cincinnati, OH, USA). Patty's Toxicology (5th Edition), Volume 8, 699-1080. Editor(s): Bingham, Eula; Cohrssen, Barbara; Powell, Charles H. John Wiley & Sons, Inc.: New York, N. Y. ISBN: 0-471-31943-0 (English) 2001. CODEN: 69CWST.
- The recognition and anticipation of potential occupational health AΒ problems, followed by assessment of occupational health risks based on chem., phys., or biol. properties of toxic agents and their potential contact or exposure under use conditions, in the practice of industrial hygiene and toxicol. for worker populations at risk is discussed. Topics covered include: background (Industrial Classification, Occupational Classification Codes, Chem. Master, Facilities, Exposure, and Trade Named Ingredients files); data source considerations; data display considerations; calcn. and display of ests. (industry-specific exposure concn. by facility employment size, industry-specific exposure concns., all industries exposure concn. by facility employment size, summary est.). appendix displays information on the industrial distribution potential occupational exposures to >300 selected chem. agents or groups of agents in 290 tables.

- IT 1309-37-1, Iron oxide (Fe2O3),
 biological studies 1309-48-4, Magnesium
 oxide (MgO), biological studies 1344-28-1
 , Aluminum oxide, biological studies
 7722-84-1, Hydrogen peroxide, biological
 studies 10102-43-9, Nitric oxide, biological studies
 10102-44-0, Nitrogen dioxide, biological
 studies
 - (industry-specific workplace populations at risk from exposure to or contact with toxic chem. agents)
- L54 ANSWER 4 OF 13 HCA COPYRIGHT 2003 ACS on STN
 137:227842 Assignment of skin notation for maximum allowable
 concentration (MAC) list in Poland. Czerczak, Slawomir; Kupczewska,
 Malgorzata (Nofer Institute of Occupational Medicine, Lodz, Pol.).
 Applied Occupational and Environmental Hygiene, 17(3), 187-199
 (English) 2002. CODEN: AOEHE9. ISSN: 1047-322X. Publisher: Taylor & Francis Ltd..
- AB Org. chems. from the Polish max. allowable concn. (MAC) list were analyzed for skin notation. It can be concluded that the dermal dose LD50s detd. on exptl. animals ought to be adopted as the fundamental criterion for providing a substance with the percutaneous absorption notation in the MAC list. All chems. with LD50s value below 1000 mg/kg should be provided with the Sk index in the MAC list. For other chems., a skin notation would be considered when repeated human and dermal application tests have shown significant systemic effects following exposure. When information on the characteristics specified above were not available, physicochem. data required to calc. the flow (soly., octanol/water partition coeff., mol. wt.) were obtained to consider a skin notation.
- 1T 1344-28-1, Aluminum trioxide, biological
 studies 7722-84-1, Hydrogen peroxide,
 biological studies 10102-43-9, Nitrogen oxide (NO),
 biological studies 10102-44-0, Nitrogen oxide (NO2
), biological studies
 (assignment of skin notation for max. allowable concn. list in
 Poland)
- L54 ANSWER 5 OF 13 HCA COPYRIGHT 2003 ACS on STN

 136:394474 Method of forming a layer comprising tungsten oxide in capacitor and field effect transistor. Yang, Haining (Micron Technology, Inc., USA). U.S. US 6391801 B1 20020521, 12 pp. (English). CODEN: USXXAM. APPLICATION: US 1999-388731 19990901.

 AB The invention includes capacitors, capacitor forming methods, field effect transistors, and field effect transistor forming methods. A method of forming a layer including W oxide includes forming a 1st layer including W nitride over a substrate. The W nitride is oxidized under conditions effective to form a 2nd layer at least a majority of which is W trioxide. A capacitor forming method includes forming a 1st capacitor electrode layer over a substrate.

A 2nd layer including W nitride is formed over the 1st capacitor electrode layer. A 3rd capacitor electrode layer is formed over the 2nd layer. The 2nd layer is oxidized under conditions effective to transform at least some of the W nitride into a W trioxide comprising capacitor dielec. layer. Other capacitor forming methods are contemplated. The invention also includes capacitors formed by these and other methods. A method of forming a field effect transistor includes forming a W nitride comprising layer proximate .qtoreq.1 of a semiconductive channel region or a conductive gate layer. The W nitride comprising layer is oxidized under conditions effective to transform at least some of the W nitride to a W oxide comprising gate dielec. layer. A transistor gate is provided operably proximate the gate dielec. layer, and source/drain regions are provided operably proximate the transistor gate. 11113-84-1, Ruthenium oxide

IT

(capacitor electrode; method of forming a tungsten oxide layer in capacitor and FET by oxidn. of tungsten nitride layer formed by low pressure CVD)

RN11113-84-1 HCA

(CA INDEX NAME) CNRuthenium oxide (9CI)

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

7722-84-1, Hydrogen peroxide, processes IT

10102-43-9, Nitrogen oxide (NO), processes

10102-44-0, Nitrogen oxide (NO2), processes

(method of forming a tungsten oxide layer in capacitor and FET by oxidn. of tungsten nitride layer formed by low pressure CVD)

7722-84-1 HCA RN

Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CN

HO-OH

10102-43-9 HCA · RN

Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CN

N = 0

RN 10102-44-0 HCA

Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN

0 - N = 0

H01L021-31 IC ICM

H01L021-44; H01L021-469

NCL 438785000

CC 76-10 (Electric Phenomena)

Section cross-reference(s): 57

7429-90-5, Aluminum, uses 7440-06-4, Platinum, uses IT Rhodium, uses 7440-32-6, Titanium, uses 7440-33-7, Tungsten, 7440-50-8, Copper, uses 11113-84-1,

Ruthenium oxide 11116-16-8, Titanium nitride 12680-36-3, Rhodium oxide 13463-67-7, Titanium oxide, uses (capacitor electrode; method of forming a tungsten oxide layer in capacitor and FET by oxidn. of tungsten nitride layer formed by low pressure CVD)

7722-84-1, Hydrogen peroxide, processes
7782-44-7, Oxygen, processes 10024-97-2, Nitrogen oxide (N2O), processes 10028-15-6, Ozone, processes 10102-43-9,
Nitrogen oxide (NO), processes 10102-44-0, Nitrogen oxide (NO2), processes

(method of forming a tungsten oxide layer in capacitor and FET by oxidn. of tungsten nitride layer formed by low pressure CVD)

L54 ANSWER 6 OF 13 HCA COPYRIGHT 2003 ACS on STN

134:282739 Procedure for the treatment of malodorous gas. Han,
Seong-Hwan; Jung, Kwang-Deog; Joo, Oh-Shim; Cho, Seong-Hoon; Oh,
Jun-Woo (Korea Institute of Science and Technology, S. Korea). Ger.
Offen. DE 10049545 A1 20010412, 10 pp. (German). CODEN: GWXXBX.
APPLICATION: DE 2000-10049545 20001006. PRIORITY: KR 1999-43008
19991006.

AB Malodorous gases are treated economically and efficiently with ambient temp. and pressure by a catalytic absorption and oxidn. procedure, which cover: (a) in-contact-bringing the malodorous gases with a scrubbing water, contg. a catalyst, in order to absorb the malodorous components catalytically, and (b) to the resulting soln., contg. the malodorous components, a catalytic oxidn. subject to their contacting with an oxidizing agent in the presence of the catalyst at 0-100.degree. under an ambient pressure whereby the catalyst is an active metallic element enclosure, selected from alkali -, alk.-earth and/or transition metals, and an optional oxide substrate.

TT 7722-84-1, Hydrogen peroxide, reactions
10102-43-9, Nitrogen oxide (NO), reactions
10102-44-0, Nitrogen oxide (NO2), reactions
(oxidizer; procedure for treatment of malodorous gas)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N=O

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1309-48-4, Magnesium oxide, uses
IT
     1332-37-2, Iron oxide, uses
     1344-28-1, Alumina, uses
        (procedure for treatment of malodorous gas)
     1309-48-4
               HCA
RN
     Magnesium oxide (MgO) (9CI) (CA INDEX NAME)
CN
Mq = 0
RN
     1332-37-2 HCA
     Iron oxide (8CI, 9CI) (CA INDEX NAME)
CN
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***.
RN
     1344-28-1 HCA
     Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME)
CN
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
     B01D053-77; B01D053-86
IC
     48-1 (Unit Operations and Processes)
CC
     Section cross-reference(s): 59, 67
     7681-52-9, Sodium hypochlorite 7722-84-1, Hydrogen
IT
     peroxide, reactions 7782-44-7, Oxygen, reactions
     10024-97-2, Nitrogen oxide (N2O), reactions
                                                    10028-15-6, Ozone,
     reactions 10102-43-9, Nitrogen oxide (NO), reactions
     10102-44-0, Nitrogen oxide (NO2), reactions
     11104-93-1, Nitrogen oxide, reactions
        (oxidizer; procedure for treatment of malodorous gas)
     1304-28-5, Barium oxide, uses 1304-76-3, Bismuth oxide, uses 1305-78-8, Calcium oxide, uses 1306-19-0, Cadmium oxide, uses
IT
     1309-48-4, Magnesium oxide, uses
     1312-43-2, Indium oxide
                               1314-11-0, Strontium oxide, uses
     1314-13-2, Zinc oxide, uses 1314-23-4, Zirconium oxide, uses
     1314-35-8, Tungsten oxide, uses
                                        1314-61-0, Tantalum oxide
     1327-33-9, Antimony oxide 1332-29-2, Tin oxide 1332-37-2
      Iron oxide, uses
                          1335-25-7, Lead oxide ,
     1344-28-1, Alumina, uses 7631-86-9, Silica, uses
     11098-99-0, Molybdenum oxide 11099-11-9, Vanadium oxide
     11118-57-3, Chromium oxide 11129-60-5, Manganese oxide
     12024-21-4, Gallium oxide 12055-23-1, Hafnium oxide
                     12640-89-0, Selenium oxide 12777-38-7, Arsenic
     Niobium oxide
     oxide
             13463-67-7, Titanium oxide, uses 157858-56-5, Germanium
     oxide
        (procedure for treatment of malodorous gas)
     ANSWER 7 OF 13 HCA COPYRIGHT 2003 ACS on STN
L54
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133:25621 Low temperature CVD processes for preparing ferroelectric films using bi aryls. Hintermaier, Frank S.; Van Buskirk, Peter C.; Roeder, Jeffrey F.; Hendrix, Bryan C.; Baum, Thomas H.; Desrochers, Debra A. (Infineon Technologies A.-G., Germany; Advanced Technology Materials, Inc.). PCT Int. Appl. WO 2000034550 A2 20000615, 37 pp. DESIGNATED STATES: W: CN, JP, KR; RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE. (English). CODEN:

603-33-8,

APPLICATION: WO 1999-US28833 19991206. PRIORITY: US PIXXD2. 1998-208544 19981209. CVD was used to form a film of Bi oxide, Sr oxide, and Ta oxide on a ABheated substrate by decompg. the precursors of these oxides adjacent to the substrate. The precursor of Bi oxide is a Bi complex which includes at least one aryl group and is decompd. at a decompn. temp. <450.degree.. The film of Bi, Sr, and Ta oxides obtained by low-temp. CVD is predominantly nonferroelec., but can be converted into a ferroelec. film by a subsequent heating process. 7722-84-1, Hydrogen peroxide, uses IT 10102-43-9, Nitric oxide, uses 10102-44-0, Nitrogen dioxide, uses (low temp. CVD processes for prepg. ferroelec. films using bismuth aryls and annealing) RN7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CN HO-OH RN10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CNN = 0RN 10102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CNO - N = OIT 1309-48-4, Magnesia, uses 1344-28-1, Alumina, uses (substrate; low temp. CVD processes for prepg. ferroelec. films using bismuth aryls and annealing) 1309-48-4 HCA RN Magnesium oxide (MgO) (9CI) (CA INDEX NAME) CN Mq = 0RN1344-28-1 HCA Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) CN*** STRUCTURE DIAGRAM IS NOT AVAILABLE *** IC ICM C23C016-00 76-8 (Electric Phenomena) CCSection cross-reference(s): 75 67-63-0, Isopropanol, uses 109-99-9, uses 111-65-9, Octane, uses IT 111-84-2, Nonane 112-40-3, Dodecane 112-49-2D, Triglyme, strontium complex 124-18-5, Decane 143-24-8, Tetraglyme

143-24-8D, Tetraglyme, strontium complex 437-29-6

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Triphenylbismuth 603-33-8D, Triphenylbismuth, derivs.
                                                                 629-50-5,
                 629-59-4, Tetradecane 1120-21-4, Undecane
     Tridecane
     3030-47-5D, strontium complex 3083-10-1D, N,N,N',N'',N''',N'''-Hexamethyltriethylenetetramine, strontium complex 5142-75-6
     7440-37-1, Argon, uses 7440-59-7, Helium, uses
                                                         7440-69-9D,
     Bismuth, diaryl compds., uses 7722-84-1, Hydrogen
     peroxide, uses
                      7727-37-9, Nitrogen, uses 7782-44-7,
                    10024-97-2, Nitrogen oxide (N2O), uses
     Oxygen, uses
                                                              10028-15-6,
                   10050-08-5 10102-43-9, Nitric oxide, uses
     Ozone, uses
     10102-44-0, Nitrogen dioxide, uses
     12033-49-7, Nitrogen oxide (NO3)
                                         26919-48-2
                                                      33397-21-6
     34422-57-6
                  36830-74-7 36830-74-7D, adduct
                                                      59344-64-8
     126769-20-8
                   146096-43-7
                                  150939-76-7
                                                177580-53-9
                                                              271788-83-1
     271789-40-3
                   271789-42-5
                                  271789-43-6
                                                271789-44-7
        (low temp. CVD processes for prepg. ferroelec. films using
        bismuth aryls and annealing)
     11103-32-5P, Bismuth iron lanthanum titanium oxide (Bi4FeLaTi3015)
IT
     11103-33-6P, Bismuth iron praseodymium titanium oxide
     (Bi4FePrTi3O15)
                       12010-42-3P, Bismuth iron oxide
     (BiFeO3)
                12010-48-9P, Bismuth niobium potassium oxide (BiNb5K2015)
     12010-77-4P, Bismuth titanium oxide (Bi4Ti3O12)
                                                        12047-47-1P,
    Barium bismuth titanium oxide (Ba2Bi4Ti5O18) 12048-25-8P, Bismuth
    potassium titanium oxide (BiKTi2O6)
                                          12161-72-7P, Barium bismuth
    vanadium oxide (Ba2BiVO6)
                                  12231-09-3P, Barium bismuth niobium
                         12231-10-6P, Barium bismuth tantalum oxide
     oxide (Ba2BiNb06)
     (Ba2BiTaO6)
                   12231-66-2P, Barium bismuth molybdenum oxide
     (Ba3Bi2MoO9)
                    12231-67-3P, Barium bismuth tungsten oxide
                   12232-95-0P, Bismuth manganese oxide (BiMnO3)
     (Ba3Bi2WO9)
     12233-01-1P, Bismuth lead niobium oxide (BiPb2Nb06)
                                                            12233-04-4P,
    Bismuth lead tantalum oxide (BiPb2TaO6)
                                                12233-27-1P, Bismuth lead
    molybdenum oxide (Bi2Pb3MoO9)
                                      12297-25-5P, Barium bismuth titanium
                           12297-31-3P, Bismuth calcium titanium oxide
    oxide (BaBi4Ti4O15)
     (Bi4CaTi4O15)
                     12297-32-4P, Bismuth lead titanium oxide
     (Bi4PbTi4O15)
                     12297-33-5P, Bismuth strontium titanium oxide
     (Bi4SrTi4O15)
                     12297-34-6P, Bismuth iron titanium oxide
                     12297-36-8P, Bismuth iron titanium oxide
     (Bi5FeTi3O15)
                      12350-18-4P, Bismuth tantalum titanium oxide
     (Bi9Fe5Ti3O27)
     (Bi3TaTi09)
                   12431-25-3P, Bismuth holmium titanium oxide
     (Bi3HoTi3O12)
                     12431-26-4P, Bismuth lanthanum titanium oxide
                     12431-28-6P, Bismuth praseodymium titanium oxide
     (Bi3LaTi3O12)
                     12441-60-0P, Bismuth calcium titanium oxide
     (Bi3PrTi3O12)
     (Bi4Ca2Ti5O18)
                      12441-63-3P, Bismuth lead titanium oxide
     (Bi4Pb2Ti5O18)
                      12441-64-4P, Bismuth strontium titanium oxide
                      12441-66-6P, Bismuth calcium iron titanium oxide
     (Bi4Sr2Ti5O18)
                       12441-67-7P, Bismuth iron lead titanium oxide
     (Bi5CaFeTi4O18)
     (Bi5FePbTi4O18)
                       12441-68-8P, Bismuth iron strontium titanium oxide
     (Bi5FeSrTi4018)
                       12448-50-9P, Barium bismuth iron titanium oxide
                       12774-73-1P, Bismuth niobium titanium oxide
     (BaBi5FeTi4O18)
                   13595-86-3P, Bismuth tungsten oxide (Bi2WO6)
     (Bi3NbTiO9)
    50811-07-9P, Bismuth strontium tantalum oxide (Bi2SrTa2O9)
    51403-91-9P, Bismuth niobium strontium oxide (Bi2Nb2SrO9)
    61163-38-0P, Bismuth lead tungsten oxide (Bi2Pb3WO9) 156832-05-2P,
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Bismuth niobium strontium tantalum oxide (Bi2Nb0-2SrTa0-2O9)
     167773-21-9P, Bismuth lead vanadium oxide (BiPb2VO6)
                                                            187239-99-2P
     219534-62-0P
                    219534-64-2P
                                   219534-66-4P
                                                  219534-68-6P
     219534-70-0P
                    219534-72-2P
                                   219534-74-4P, Bismuth iron titanium
     oxide (Bi6FeTi3O18)
                           219534-76-6P, Barium bismuth molybdenum oxide
                    219534-78-8P, Barium bismuth tungsten oxide
     (Ba6BiMoO18)
                   219534-79-9P, Bismuth lead molybdenum oxide
     (Ba6BiW018)
     (BiPb6MoO18)
                    219534-80-2P, Bismuth lead tungsten oxide (BiPb6WO18)
        (low temp. CVD processes for prepg. ferroelec. films using
        bismuth aryls and annealing)
     1303-00-0, Gallium arsenide, uses 1309-48-4, Magnesia,
            1314-23-4, Zirconia, uses 1344-28-1,
     Alumina, uses
                     12033-89-5, Silicon nitride, uses
     12047-27-7, Barium titanate, uses
                                         12060-00-3, Lead titanate
     12060-59-2, Strontium titanate
        (substrate; low temp. CVD processes for prepq. ferroelec. films
        using bismuth aryls and annealing)
     ANSWER 8 OF 13 HCA COPYRIGHT 2003 ACS on STN
          Exposure limits for health - inorganic compounds. Yaws, Carl
     L.; Sheth, Sachin D.; Han, Mei (Lamar Univ., Beaumont, TX, USA).
     Handbook of Chemical Compound Data for Process Safety, 210-214.
                                                     CODEN: 64MXAT.
     Gulf Publishing: Houston, Tex. (English) 1997.
     Results for recommended and permissible exposure limits in air to
     safeguard health are presented for major inorg. chem. compds.
     Results are displayed in an easy-to-use table which is esp.
     applicable for rapid engineering use. The inorg. chems. encompass
     Aq to Zr compds.
     1309-48-4, Magnesium oxide (MgO
     ), biological studies 1344-28-1, Aluminum
     oxide, biological studies 7722-84-1,
    Hydrogen peroxide, biological studies
     10102-43-9, Nitric oxide, biological studies
     10102-44-0, Nitrogen dioxide, biological
     studies
        (recommended and permissible exposure limits for inorg. compds.
        in workplace air to safeguard health)
     1309-48-4
               HCA
     Magnesium oxide (MgO) (9CI) (CA INDEX NAME)
Mq = 0
     1344-28-1 HCA
     Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME)
    STRUCTURE DIAGRAM IS NOT AVAILABLE ***
     7722-84-1 HCA
    Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
HO-OH
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RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

 $O-N \longrightarrow O$

CC 59-5 (Air Pollution and Industrial Hygiene) Section cross-reference(s): 4, 49

74-90-8, Hydrogen cyanide, biological studies IT75-15-0, Carbon disulfide, biological studies 75-44-5, Carbonic dichloride 124-38-9, Carbon dioxide, biological studies 143-33-9, Sodium cyanide 151-50-8, Potassium cyanide 302-01-2, Hydrazine, biological studies 630-08-0, Carbon monoxide, biological studies 1306-19-0, Cadmium oxide, biological studies 1309-48-4, Magnesium oxide (MgO), biological 1310-58-3, Potassium hydroxide, biological studies 1310-73-2, Sodium hydroxide, biological studies 1314-13-2, Zinc oxide, biological studies 1314-80-3, Phosphorus pentasulfide 1344-28-1, Aluminum oxide, biological 2551-62-4 2699-79-8, Sulfuryl fluoride studies 7429-90-5, Aluminum, biological studies 7439-92-1, Lead, biological studies 7439-96-5, Manganese, biological studies 7439-98-7, Molybdenum, biological studies 7440-02-0, Nickel, biological studies 7440-06-4, Platinum, biological studies 7440-16-6, Rhodium, biological studies 7440-21-3, Silicon, biological studies 7440-22-4, Silver, biological studies 7440-25-7, Tantalum, biological studies 7440-31-5, Tin, biological studies Tungsten, biological studies 7440-36-0, Antimony, biological 7440-38-2, Arsenic, biological studies 7440-41-7, Beryllium, biological studies 7440-43-9, Cadmium, biological studies 7440-44-0, Carbon, biological studies 7440-47-3, Chromium, biological studies 7440-48-4, Cobalt, biological studies 7440-50-8, Copper, biological studies 7440-58-6, Hafnium, biological studies 7440-61-1, Uranium, biological studies 7440-65-5, Yttrium, biological studies 7440-67-7, Zirconium, biological studies 7440-74-6, Indium, biological studies 7446-09-5, Sulfur dioxide, biological studies 7553-56-2, Iodine, biological studies 7580-67-8, Lithium hydride 7616-94-6, Perchloryl fluoride 7631-86-9, Silicon dioxide, biological studies 7637-07-2, Boron trifluoride, biological studies 7646-85-7, Zinc chloride (ZnCl2), biological studies 7647-01-0, Hydrogen chloride, biological studies 7664-39-3, Hydrogen fluoride, biological 7664-41-7, Ammonia, biological studies 7664-93-9. Sulfuric acid, biological studies 7681-49-4, Sodium fluoride, biological studies 7697-37-2, Nitric acid, biological studies 7705-08-0, Ferric chloride, biological studies 7722-84-1,

Hydrogen peroxide, biological studies 7726-95-6, Bromine, biological studies 7758-94-3, Ferrous chloride 7782-41-4, Fluorine, biological studies 7782-49-2, Selenium, biological studies 7782-50-5, Chlorine, biological studies 7783-06-4, Hydrogen sulfide, biological studies 7783-07-5, 7783-41-7, Fluorine oxide 7783-54-2, Nitrogen Hydrogen selenide 7783-79-1, Selenium hexafluoride 7783-80-4, trifluoride Tellurium hexafluoride 7784-42-1, Arsine 7790-91-2, Chlorine 7803-51-2, Phosphine 7803-52-3, Stibine 7803-62-5, trifluoride Silane, biological studies 10024-97-2, Nitrous oxide, biological 10025-87-3, Phosphorus oxychloride 10026-13-8, Phosphorus pentachloride 10028-15-6, Ozone, biological studies 10035-10-6, Hydrogen bromide, biological studies 10049-04-4. Chlorine dioxide 10102-43-9, Nitric oxide, biological studies 10102-44-0, Nitrogen dioxide, biological studies 10546-01-7, Sulfur pentafluoride 12125-02-9, Ammonium chloride, biological studies 13463-39-3, Nickel carbonyl 13494-80-9, Tellurium, biological 13463-40-6, Iron pentacarbonyl 19287-45-7, Diborane 19624-22-7, Pentaborane 20762-59-8, Phosphorus tetrachloride (recommended and permissible exposure limits for inorg. compds.

L54 ANSWER 9 OF 13 HCA COPYRIGHT 2003 ACS on STN

in workplace air to safeguard health)

121:262443 French limiting values for occupational exposure to chemicals. Anon. (Fr.). Cahiers de Notes Documentaires, 153, 557-74 (French) 1993. CODEN: CNDIBJ. ISSN: 0007-9952.

- AB Limit values (suggested limiting values and max. permissible values) for occupational exposure to chems., including carcinogens, which have been published by the French Labor Ministry are presented in one table. This table is preceded by information on the following points: monitoring of workplace atmospheres (sampling and anal.; aerosols); permitted values (definitions and aims; additivity convention; elements and compds.; limiting occupational exposure values; carcinogens); mandatory values; and values recommended by the French National Health Insurance Fund (CNAM).
- 1309-37-1, Ferric oxide, biological studies
 1309-48-4, Magnesium oxide, biological
 studies 1344-28-1, Aluminum oxide (
 Al203), biological studies 7722-84-1,
 Hydrogen peroxide, biological studies
 10102-43-9, Nitrogen oxide (NO), biological studies
 10102-44-0, Nitrogen dioxide, biological
 studies

(occupational exposure; occupational exposure and stds. for limiting workplace concns. of chems. in France)

L54 ANSWER 10 OF 13 HCA COPYRIGHT 2003 ACS on STN
116:135528 Performance-oriented packaging standards; changes to
classification, hazard communication, packaging and handling
requirements based on UN standards and agency initiative. (United

States Dept. of Transportation, Washington, DC, 20590-0001, USA). Federal Register, 55(246), 52402-729 (English) 21 Dec 1990. CODEN: FEREAC. ISSN: 0097-6326.

- AB The hazardous materials regulations under the Federal Hazardous Materials Transportation Act are revised based on the United Nations recommendations on the transport of dangerous goods. The regulations cover the classification of materials, packaging requirements, and package marking, labeling, and shipping documentation, as well as transportation modes and handling, and incident reporting. Performance-oriented stds. are adopted for packaging for bulk and nonbulk transportation, and SI units of measurement generally replace US customary units. Hazardous material descriptions and proper shipping names are tabulated together with hazard class, identification nos., packing group, label required, special provisions, packaging authorizations, quantity limitations, and vessel stowage requirements.
- L54 ANSWER 11 OF 13 HCA COPYRIGHT 2003 ACS on STN
- 112:39443 Comparison of methods for calculating the composition and thermodynamic properties of the combustion products of organic fuels. Mika, V. I.; Munvez, S. S.; Prokop, A. S.; Vujevic, V.; Lekic, A.; Popovic, A. (Mosk. Energ. Inst., Moscow, USSR). Teplofizika Vysokikh Temperatur, 27(4), 702-7 (Russian) 1989. CODEN: TVYTAP. ISSN: 0040-3644.
- AB Three methods were evaluated for the calcn. of the thermodn. properties and compn. of products of combustion of CH4 and coal at 1000-3000 K and 0.1 MPa in the presence of K2CO3 (ionization additive). There were no substantial differences among the results obtained by these methods, provided the input data and condensation models were the same. Condensation models have a much larger impact on the result.
- 1309-37-1, Ferric oxide, uses and miscellaneous
 1309-48-4, Magnesium oxide, uses and
 miscellaneous 1344-28-1, Alumina, uses and
 miscellaneous 7722-84-1, Hydrogen
 peroxide, uses and miscellaneous 10102-43-9,
 Nitric oxide, uses and miscellaneous 10102-44-0, Nitrogen
 oxide (NO2), uses and miscellaneous

(in combustion products of methane and coal, abundance of, calcn. of, methods for, comparison of)

RN 1309-37-1 HCA

CN Iron oxide (Fe2O3) (8CI, 9CI) (CA INDEX NAME)

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

RN 1309-48-4 HCA

CN Magnesium oxide (MgO) (9CI) (CA INDEX NAME)

Mg = 0RN 1344-28-1 HCA CNAluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) *** STRUCTURE DIAGRAM IS NOT AVAILABLE *** RN 7722-84-1 HCA CNHydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) HO-OH RN 10102-43-9 HCA CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) N = ORN10102-44-0 HCA CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) O-N=O51-12 (Fossil Fuels, Derivatives, and Related Products) CC Section cross-reference(s): 69 124-38-9, Carbon dioxide, uses and miscellaneous IT630-08-0, Carbon monoxide, uses and miscellaneous 1305-78-8, Calcium oxide, uses and miscellaneous 1309-37-1, Ferric oxide, uses and miscellaneous 1309-48-4, Magnesium oxide , uses and miscellaneous 1310-58-3, Potassium hydroxide, uses and miscellaneous 1310-73-2, Sodium hydroxide, uses and miscellaneous miscellaneous 1333-74-0, Hydrogen, uses and miscellaneous 1344-28-1, Alumina, uses and miscellaneous 3170-83-0, Hydroperoxo 3352-57-6, Hydroxyl, uses and miscellaneous 7429-90-5, Aluminum, uses and miscellaneous 7439-89-6, Iron, uses and miscellaneous 7439-95-4, Magnesium, uses and miscellaneous 7440-09-7, Potassium, 7440-21-3, Silicon, uses and miscellaneous uses and miscellaneous 7440-23-5, Sodium, uses and miscellaneous 7440-37-1, Argon, uses and miscellaneous 7440-44-0, Carbon, uses and miscellaneous 7440-70-2, Calcium, uses and miscellaneous 7446-09-5, Sulfur dioxide, uses and miscellaneous 7446-11-9, Sulfur trioxide, uses 7631-86-9, Silica, uses and miscellaneous and miscellaneous 7704-34-9, Sulfur, uses and miscellaneous 7722-84-1, Hydrogen peroxide, uses and miscellaneous 7727-37-9, Nitrogen, uses and miscellaneous 7732-18-5, Water, uses and miscellaneous 7778-80-5, Potassium sulfate, uses and miscellaneous 7782-44-7, Oxygen, uses and miscellaneous 10006-28-7, Potassium silicate (K2SiO3) 10024-97-2, Nitrous oxide,

uses and miscellaneous 10102-43-9, Nitric oxide, uses and

miscellaneous 10102-44-0, Nitrogen oxide (NO2),

uses and miscellaneous 12004-36-3, Aluminum oxide (Al2O) 12136-45-7, Potassium oxide, uses and miscellaneous 13827-32-2, Sulfur monoxide 14457-64-8, Aluminum oxide (AlO) 18624-44-7, Ferrous hydroxide

(in combustion products of methane and coal, abundance of, calcn. of, methods for, comparison of)

L54 ANSWER 12 OF 13 HCA COPYRIGHT 2003 ACS on STN

110:218230 Air contaminants. (United States Occupational Safety and Health Administration, Washington, DC, 20210, USA). Federal Register, 54(12, Bk. 2), 2332-983 (English) 19 Jan 1989. CODEN: FEREAC. ISSN: 0097-6326.

AB Under the Federal Occupational Safety and Health act, OSHA is amending existing air containment stds. and setting new permissible exposure limits for toxic substances commonly used in the workplace.

1309-37-1, Iron oxide, biological studies 1309-48-4, Magnesium oxide, biological studies 1344-28-1, .alpha.-Alumina, biological studies 7722-84-1, Hydrogen peroxide, biological studies 10102-43-9, Nitric oxide, biological studies 10102-44-0, Nitrogen dioxide, biological studies

(air pollution by, occupational exposure to, stds. for, in USA)

- L54 ANSWER 13 OF 13 HCA COPYRIGHT 2003 ACS on STN 85:83876 Approximation coefficients of the thermodynamic potential for substances formed by aluminum, boron, carbon, calcium, chlorine, copper, fluorine, hydrogen, potassium, lithium, magnesium, nitrogen, sodium, oxygen, phosphorus, sulfur, silicon, and titanium atoms in a temperature range up to 6000 K. Rozhdestvenskii, I. B.; Gutov, V. N.; Zhigul'skaya, N. A. (USSR). Sbornik Trudov Energeticheskii Institut imeni G. M. Krzhizhanovskogo, 7, 88-121 (Russian) 1973. CODEN: STGIDG.
- AB By using published thermodn. data (handbooks, thermochem. tables) the approxn. coeffs. for calcg. free energy function (F-H)/T are given for >1000 compds. (consisting of the 18 title elements) in solid, liq., and gaseous states were computer calcd. The enthalpies of the compds. are listed also.
- 1309-48-4, properties 1344-28-1, properties 7722-84-1, properties 10102-43-9, properties 10102-44-0, properties (thermodn. of)
- => d 155 1-28 cbib abs hitstr hitind
- L55 ANSWER 1 OF 28 HCA COPYRIGHT 2003 ACS on STN
 137:283406 Desulfurization apparatus and method for efficient
 desulfurization even in presence of nitrogen monooxide. Yoshikawa,
 Masaaki; Yasutake, Akinori; Kurisaki, Takashi; Kobayashi, Keiko

(Osaka Gas Co., Ltd., Japan; Mitsubishi Heavy Industries, Ltd.). Jpn. Kokai Tokkyo Koho JP 2002301335 A2 20021015, 9 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2001-105384 20010404.

The flue gas desulfurization app. comprises a desulfurization tower contg. a porous carbon material selected from activated carbon and activated carbon fibers and is further provided with a NO2 gas introduction app. for introducing NO2 into the tower. Alternatively, a NO oxidn. app. for oxidizing NO to NO2 is installed in the upstream side of the tower. The NO oxidn. app. may comprise an elec. discharge oxidn. means, an oxidn. catalyst, an ozone oxidn. means, and/or a H2O2 oxidn. means. Desulfurization is carried out by bringing a SO2-contg. flue gas into contact with the porous carbon material while introducing NO2 gas into the tower. While desulfurization inhibition by NO being suppressed, SO2 can be efficiently removed from a flue gas emitted out of a boiler, a thermal power plant, a variety of plants and so on.

IT 10102-44-0, Nitrogen dioxide,

miscellaneous

(desulfurization in presence of; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N==O

IT 7722-84-1, Hydrogen peroxide, processes

(nitrogen monooxide oxidn. by; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

но-он

IT 10102-43-9, Nitrogen monooxide, processes

(**oxidn**. in desulfurization; flue gas desulfurization app. and method using carbon type porous material with means for supplying **nitrogen dioxide**)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

IC ICM B01D053-86

CC 59-4 (Air Pollution and Industrial Hygiene)

IT Carbon fibers, uses

(activated; flue gas desulfurization app. and method using carbon

type porous material with means for supplying **nitrogen dioxide**)

IT Flue gases

(boiler, sulfur oxide removal from; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

IT Flue gas desulfurization

(flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

IT Electric discharge

Oxidation catalysts

(nitrogen monooxide oxidn. by; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

IT Oxidation

(of nitrogen monooxide; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

IT 7440-44-0, Carbon, uses

(activated; flue gas desulfurization app. and method using carbon type porous material with means for supplying **nitrogen** dioxide)

IT 10102-44-0, Nitrogen dioxide,

miscellaneous

(desulfurization in presence of; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

TT 7647-01-0, Hydrogen chloride, processes 7697-37-2, Nitric acid, processes 7790-92-3, Hypochlorous acid 13465-41-3, Permanganic acid

(nitrogen monooxid oxidn. assisted by; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

IT 7722-84-1, Hydrogen peroxide, processes

7782-44-7, Oxygen, processes 10028-15-6, Ozone, processes (nitrogen monooxide oxidn. by; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

10102-43-9, Nitrogen monooxide, processes
(oxidn. in desulfurization; flue gas desulfurization
app. and method using carbon type porous material with means for
supplying nitrogen dioxide)

IT 7446-09-5, Sulfur dioxide, processes

(removal from flue gases; flue gas desulfurization app. and method using carbon type porous material with means for supplying nitrogen dioxide)

L55 ANSWER 2 OF 28 HCA COPYRIGHT 2003 ACS on STN

136:181951 Effect of overexpression of Bcl-2 on cellular

oxidative damage, nitric oxide

production, antioxidant defenses, and the proteasome. Lee, MoonHee;

Hyun, Dong-Hoon; Marshall, Karyn-Ann; Ellerby, Lisa M.; Bredesen, Dale E.; Jenner, Peter; Halliwell, Barry (Wolfson Centre for Age-Related Diseases, Guy's, King's and St. Thomas' School of Biomedical Sciences, King's College London, London, UK). Free Radical Biology & Medicine, 31(12), 1550-1559 (English) 2001. ISSN: 0891-5849. Publisher: Elsevier Science Inc.. CODEN: FRBMEH. Bcl-2 is a gene family involved in the suppression of apoptosis in AΒ response to a wide range of cellular insults. Multiple papers have suggested a link between Bcl-2 and oxidative damage/antioxidant protection. The authors therefore examd. parameters of antioxidant defense and oxidative damage in two different cell lines, NT-2/D1 (NT-2) and SK-N-MC, overexpressing Bcl-2 as compared with vector-only controls. Bcl-2 transfectants of both cell lines were more resistant to H2O2 and showed increases in GSH level and Cu/Zn-superoxide dismutase (SOD1) activity, but not in Mn-superoxide dismutase, glutathione peroxidase, or glutathione reductase activities. Catalase activity was increased in SK-N-MC cells. Overexpression of Bcl-2 did not significantly decrease levels of oxidative DNA damage (measured as 8-hydroxyguanine) or lipid peroxidn., but it decreased levels of 3-nitrotyrosine in both cell lines and protein carbonyls in SK-N-MC cells only. It also increased proteasome activity in both cell lines. The authors conclude that Bcl-2 raises cellular antioxidant defense status, but this is not necessarily reflected in decreased levels of oxidative damage to DNA and lipids. The ability of Bcl-2 overexpression to decrease 3-nitrotyrosine levels suggests that it may decrease formation of peroxynitrite or other reactive nitrogen species; this was confirmed as decreased prodn. of NO2-/NO3- in the transfected cells and a fall in the level of nNOS protein. 7722-84-1, Hydrogen peroxide, biological

7722-84-1, Hydrogen peroxide, biological studies 10102-43-9, Nitric oxide, biological studies (effect of overexpression of Bcl-2 on cellular oxidative damage, nitric oxide prodn., antioxidant defenses, and proteasome)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

но-он

RN 10102-43-9 HCA CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = O

CC 14-15 (Mammalian Pathological Biochemistry) Section cross-reference(s): 3, 13

ST Bcl2 cellular **oxidative** damage **nitric oxide** prodn antioxidant proteasome

IT Gene, animal Proteins

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(Bcl-2; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     Oxidation
        (biol.; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     Proteins
        (carbonyl groups; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     DNA
        (damage; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     Animal cell line
     Antioxidants
     Apoptosis
     Human
     Transcription, genetic
        (effect of overexpression of Bcl-2 on cellular oxidative
        damage, nitric oxide prodn., antioxidant
        defenses, and proteasome)
IT
     Reactive nitrogen species
        (effect of overexpression of Bcl-2 on cellular oxidative
        damage, nitric oxide prodn., antioxidant
        defenses, and proteasome)
IT
     Peroxidation
        (lipid; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     Lipids, biological studies
        (peroxidn.; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     Carbonyl group
        (protein; effect of overexpression of Bcl-2 on cellular
        oxidative damage, nitric oxide
        prodn., antioxidant defenses, and proteasome)
IT
     7727-37-9D, Nitrogen, reactive species
        (Reactive nitrogen species; effect of overexpression of Bcl-2 on
        cellular oxidative damage, nitric
        oxide prodn., antioxidant defenses, and proteasome)
IT
     9054-89-1, Superoxide dismutase
        (copper-zinc- and manganese-contg. isoenzymes; effect of
        overexpression of Bcl-2 on cellular oxidative damage,
       nitric oxide prodn., antioxidant defenses, and
        proteasome)
IT
     621-44-3, 3-Nitro-L-tyrosine
                                    5614-64-2, 8-Hydroxyguanine
    7722-84-1, Hydrogen peroxide, biological
    studies 10102-43-9, Nitric oxide, biological studies
     14797-55-8, Nitrate, biological studies 14797-65-0, Nitrite,
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biological studies 19059-14-4, Peroxynitrite 140879-24-9, Multicatalytic proteinase

(effect of overexpression of Bcl-2 on cellular **oxidative** damage, **nitric oxide** prodn., antioxidant defenses, and proteasome)

TT 70-18-8, Reduced glutathione, biological studies 9001-05-2, Catalase 9001-48-3, Glutathione reductase 9013-66-5, Glutathione peroxidase

(effect of overexpression of Bcl-2 on cellular **oxidative** damage, **nitric oxide** prodn., antioxidant defenses, and proteasome)

L55 ANSWER 3 OF 28 HCA COPYRIGHT 2003 ACS on STN

135:331301 Innovation of hydrocarbon oxidation with molecular oxygen and related reactions. Ishii, Yasutaka; Sakaguchi, Satoshi; Iwahama, Takahiro (Department of Applied Chemistry, Faculty of Engineering and High Technology Research Center, Kansai University, Suita, Osaka, 564-8680, Japan). Advanced Synthesis & Catalysis, 343(5), 393-427 (English) 2001. CODEN: ASCAF7. ISSN: 1615-4150. Publisher: Wiley-VCH Verlag GmbH.

AΒ A review with refs. An innovation of the aerobic oxidn. of hydrocarbons through catalytic carbon radical generation under mild conditions was achieved by using N-hydroxyphthalimide (NHPI) as a key compd. Alkanes were successfully oxidized with O or air to valuable oxygen-contg. compds. such as alcs., ketones, and dicarboxylic acids by the combined catalytic system of NHPI and a transition metal such as Co or Mn. The NHPI-catalyzed oxidn. of alkylbenzenes with dioxygen could be performed even under normal temp. and pressure of dioxygen. Xylenes and methylpyridines were also converted into phthalic acids and pyridinecarboxylic acids, resp., ill good yields. The present oxidn. method was extended to the selective transformations of alcs. to carbonyl compds. and of alkynes to ynones. The epoxidn. of alkenes using hydroperoxides or H2O2 generated in situ from hydrocarbons or alcs. and O2 under the influence of the NHPI was demonstrated and seems to be a useful strategy for industrial applications. The NHPI method is applicable to a wide variety of org. syntheses via carbon radical intermediates. The catalytic carboxylation of alkanes was accomplished by the use of CO and O2 in the presence of NHPI. addn., the reactions of alkanes with NO, and SO2 catalyzed by NHPI provided efficient methods for the synthesis of nitroalkanes and sulfonic acids, resp. A catalytic carbon-carbon bond forming reaction was achieved by allowing carbon radicals generated in situ from alkanes or alcs. to react with alkenes under mild conditions. A table of contents in this review includes: (1) Introduction: (2) Discovery of NHPI as Carbon Radical Producing Catalyst from Alkanes: (2.1) Historical Background: (2.2) Catalysis of NHPI in Aerobic Oxidn.: (3) NHPI-Catalyzed Aerobic Oxidn.: (3.1) Oxidn. of Benzylic Compds.: (3.2) Alkane Oxidns. with Mol. Oxygen: (3.3) Oxidn. of Alkylbenzenes: (3.4) Practical Oxidn. of Methylpyridines: (3.5) Prepn. of Acetylenic Ketones via Alkyne Oxidn.: (3.6) Oxidn. of Alcs.: (3.7) Selective Oxidn. of Sulfides to Sulfoxides: (3.8)

Prodn. of Hydrogen Peroxide by Aerobic Oxidn. of Alcs.: (3.9) Epoxidn. of Alkenes using Mol. Oxygen as Terminal Oxidant: (4) Carboxylation of Alkanes with CO and O2: (5) Utilization of NOx in Org. Synthesis: (5.1) First Catalytic Nitration of Alkanes using NO2: (5.2) Reaction of NO2 with Org. Compds.: (6) Sulfoxidn. of Alkanes Catalyzed by Vanadium: (7) Carbon-Carbon Bond Forming Reaction via Catalytic Carbon Radicals Generated from Various Org. Compds. Assisted by NHPI: (7.1) Oxyalkylation of Alkenes with Alkanes and Dioxygen: (7.2) Synthesis of .alpha.-Hydroxy-.gamma.-lactones by Addn. of .alpha.-Hydroxy Carbon Radicals to Unsatd. Esters: (7.3) Hydroxyacylation of Alkenes using 1,3-Dioxolanes and Dioxygen: (8) Conclusions.

CC 27-0 (Heterocyclic Compounds (One Hetero Atom))
Section cross-reference(s): 23, 24, 25, 30

IT Nitration catalysts
(N-hydroxyphthalimide, for nit

reactions)

(N-hydroxyphthalimide, for nitration of alkanes with nitrogen dioxide; innovation of hydrocarbon oxidn. with mol. oxygen and related reactions)

IT Bond cleavage

(oxidative, catalysts, N-hydroxyphthalimide, for benzyl ethers to benzaldehyde by nitric oxide; innovation of hydrocarbon oxidn. with mol. oxygen and related

L55 ANSWER 4 OF 28 HCA COPYRIGHT 2003 ACS on STN
133:325084 Process and apparatus for decomposition of halogen-containing organic compounds. Fujisawa, Masatoshi; Kato, Yasuyoshi (Babcock-Hitachi K. K., Japan). Jpn. Kokai Tokkyo Koho JP 2000300959 A2 20001031, 6 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1999-111064 19990419.

The title process comprises oxidn. of NO contained in waste gases contg. halo-contg. org. compds. by treating with NO2 or oxidizing agents, and catalytic oxidn. of the halo-contg. org. compd. by NO2 obtained above. The oxidizing agent may contain HNO3, NH4NO3, O3, and/or H2O2. The catalyst may contain TiO2, V oxide, and oxide of Mo or W. The process is useful for decompn. of dioxins contained in incinerator flue gases.

7722-84-1, Hydrogen peroxide, uses

(oxidizing agent; oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

IT 10102-43-9, Nitrogen monoxide, uses
 (oxidn. of NO by NO2 or oxidizing agent
 before catalytic oxidn. of halo-contg. org. compd. for decompn.
 of dioxin contained in incinerator flue gas)

10102-43-9 RNHCA CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) N = OIT10102-44-0, Nitrogen dioxide, uses (oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) 10102-44-0 HCA RNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CNO-N=OIC ICM B01D053-86 ICS B01D053-34; B01D053-70; B01D053-94; B01J023-28; B01J023-30 59-4 (Air Pollution and Industrial Hygiene) CCSection cross-reference(s): 67 IT Flue gases (incinerator; oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) IT Oxidation catalysts Oxidizing agents (oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) 262-12-4D, Dibenzo[b,e][1,4]dioxin, chloro derivs. IT (PCDD; oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) IT1314-35-8, Tungsten oxide, uses 11098-99-0, Molybdenum oxide 11099-11-9, Vanadium oxide 13463-67-7, Titania, uses (catalyst; oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) 6484-52-2, Ammonium nitrate, uses IT 7697-37-2, Nitric acid, uses 7722-84-1, Hydrogen peroxide, uses 10028-15-6, Ozone, uses (oxidizing agent; oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn. of dioxin contained in incinerator flue gas) 10102-43-9, Nitrogen monoxide, uses IT(oxidn. of NO by NO2 or oxidizing agent before catalytic oxidn. of halo-contg. org. compd. for decompn.

of dioxin contained in incinerator flue gas)

- IT 108-90-7, Chlorobenzene, processes 132-64-9D, Dibenzofuran, chloro
 derivs. 1746-01-6, TCDD
 (oxidn. of NO by NO2 or oxidizing agent before
 catalytic oxidn. of halo-contg. org. compd. for decompn. of
 dioxin contained in incinerator flue gas)
- L55 ANSWER 5 OF 28 HCA COPYRIGHT 2003 ACS on STN

 132:77034 Nitrite- and Peroxide-Dependent Oxidation Pathways of
 Dopamine: 6-Nitrodopamine and 6-Hydroxydopamine Formation as
 Potential Contributory Mechanisms of Oxidative Stress- and
 Nitric Oxide-Induced Neurotoxicity in Neuronal
 Degeneration. Palumbo, Anna; Napolitano, Alessandra; Barone, Paolo;
 D'Ischia, Marco (Laboratory of Biochemistry, Zoological Station,
 Naples, I-80121, Italy). Chemical Research in Toxicology, 12(12),
 1213-1222 (English) 1999. CODEN: CRTOEC. ISSN: 0893-228X.
 Publisher: American Chemical Society.
- In the presence of nitrite ions (NO2-) in phosphate buffer AB(pH 7.4) and at 37.degree., dopamine was oxidized by a variety of hydrogen peroxide (H2O2) -dependent enzymic and chem. systems to give, in addn. to black melanin-like pigments via 5,6-dihydroxyindoles, small amts. of the potent neurotoxin 6-hydroxydopamine (1) and of 6-nitrodopamine (2), a putative reaction product of dopamine with NO-derived species. Treatment of 0.5 or 1 mM dopamine with horseradish peroxidase (HRP) or lactoperoxidase (LPO) in the presence of 1 or 2 mM H2O2 with NO2- at a concn. of 0.5-10 mM resulted in the formation of 1 and 2 in up to 8 and 2 .mu.M yields, resp., depending on the substrate concn. and the NO2-: H2O2 ratio. Nitration and hydroxylation of 0.1 mM dopamine was obsd. with 1 mM NO2- using HRP and the D-glucose/glucose oxidase system to generate H2O2 in situ. In the presence of NO2 --, Fe2+-, or Fe2+/EDTA-promoted oxidns. of dopamine with H2O2 also led to the formation of 1 and 2, the apparent product ratios varying with peroxide concn. and the partitioning of the metal between EDTA and catecholamine chelates. In the presence of NO2-, Fe2+-promoted autoxidn. of dopamine gave 2 but no detectable 1. When injected into the brains of lab. rats, 2 caused sporadic behavioral changes, indicating that it could elicit a neurotoxic response, albeit to a lower extent than 1. Model expts. using tyrosinase as an oxidizing system and mechanistic considerations suggested that formation of 2 does not involve reactive nitrogen radicals but results mainly from nucleophilic attack of NO2- to dopamine quinone. Generation of 1, on the other hand, may be derives from different H2O2 -dependent pathways. Collectively, these results outline a complex interplay of NO2 -- and peroxide-dependent oxidn. pathways of dopamine, which may contribute to impair dopaminergic neurotransmission and induce cytotoxic processes in neurodegenerative disorders.
- TT 7722-84-1, Hydrogen peroxide (
 H202), biological studies 10102-43-9, Nitric
 oxide, biological studies

(nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N=== O

CC 14-10 (Mammalian Pathological Biochemistry)

IT Nervous system

(degeneration; nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide-**induced neurotoxicity in neuronal degeneration)

IT Neurotransmission

(dopaminergic; nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

IT Toxicity

(neurotoxicity; nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

IT Oxidative stress, biological

(nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

IT Melanins

(nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

IT Nerve

(toxicity; nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress-

and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

IT 7722-84-1, Hydrogen peroxide (

H2O2), biological studies 10102-43-9, Nitric

oxide, biological studies

(nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

- 1199-18-4, 6-Hydroxydopamine 21581-49-7, 6-Nitrodopamine (nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of oxidative stress- and nitric oxide-induced neurotoxicity in neuronal degeneration)
- IT 51-61-6, Dopamine, biological studies 14797-65-0, Nitrite ion, biological studies

(nitrite- and peroxide-dependent oxidn. pathways of dopamine with 6-nitrodopamine and 6-hydroxydopamine formation as potential contributory mechanisms of **oxidative** stress- and **nitric oxide**-induced neurotoxicity in neuronal degeneration)

- L55 ANSWER 6 OF 28 HCA COPYRIGHT 2003 ACS on STN
- 132:62518 Formation of nitric oxide-derived oxidants by myeloperoxidase in monocytes: pathways for monocyte-mediated protein nitration and lipid peroxidation in vivo. Hazen, Stanley L.; Zhang, Renliang; Shen, Zhongzhou; Wu, Weijia; Podrez, Eugene A.; MacPherson, Jennifer C.; Schmitt, David; Mitra, Shome N.; Mukhopadhyay, Chaitali; Chen, Yonghong; Cohen, Peter A.; Hoff, Henry F.; Abu-Soud, Husam M. (The Department of Cell Biology, the Department of Cardiology, Cleveland Clinic Foundation, Cleveland, OH, USA). Circulation Research, 85(10), 950-958 (English) 1999. CODEN: CIRUAL. ISSN: 0009-7330. Publisher: Lippincott Williams & Wilkins.
- Protein nitration and lipid peroxidn. are implicated in the AΒ pathogenesis of atherosclerosis; however, neither the cellular mediators nor the reaction pathways for these events in vivo are In the present study, we examd. the chem. pathways established. available to monocytes for generating reactive nitrogen species and explored their potential contribution to the protein nitration and lipid peroxidn. of biol. targets. Isolated human monocytes activated in media contg. physiol. relevant levels of nitrite (NO2-), a major end product of nitric oxide (NO) metab., nitrate apolipoprotein B'-100 tyrosine residues and initiate LDL lipid peroxidn. LDL nitration (assessed by gas chromatog.-mass spectrometry quantification of nitrotyrosine) and lipid peroxidn. (assessed by high-performance liq. chromatog. with online tandem mass spectrometric quantification of distinct products) required cell activation and NO2-; occurred in the presence of metal chelators, superoxide dismutase (SOD), and scavengers of hypohalous acids; and was blocked by myeloperoxidase (MPO)

inhibitors and catalase. Monocytes activated in the presence of the exogenous NO generator PAPA NONOate (Z-[N-{3-aminopropyl}-N-{n-propyl}amino]diazen-1-ium-1,2-diolate) promoted LDL protein nitration and lipid peroxidn. by a combination of pathways. At low rates of NO flux, both protein nitration and lipid peroxidn. were inhibited by catalase and peroxidase inhibitors but not SOD, suggesting a role for MPO. As rates of NO flux increased, both nitrotyrosine formation and 9-hydroxy-10,12-octadecadienoate/9-hydroperoxy-10,12-octadecadienoic acid prodn. by monocytes became insensitive to the presence of catalase or peroxidase inhibitors, but they were increasingly inhibited by SOD and methionine, suggesting a role for peroxynitrite. Collectively, these results demonstrate that monocytes use distinct mechanisms for generating NO-derived oxidants, and they identify MPO as a source of nitrating intermediates in monocytes.

10102-43-9, Nitric oxide, biological studies (derived oxidants; formation of nitric oxide-derived oxidants by myeloperoxidase in monocytes:pathways for monocyte-mediated protein nitration and lipid peroxidn. in vivo)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N == 0

TT 7722-84-1, Hydrogen peroxide, biological
studies

(formation of nitric oxide-derived oxidants by myeloperoxidase in monocytes:pathways for monocyte-mediated protein nitration and lipid peroxidn. in vivo)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

CC 14-5 (Mammalian Pathological Biochemistry)

IT Atherosclerosis

Oxidizing agents

(formation of nitric oxide-derived oxidants

by myeloperoxidase in monocytes:pathways for monocyte-mediated protein nitration and lipid peroxidn. in vivo)

IT 10102-43-9, Nitric oxide, biological studies

(derived oxidants; formation of nitric oxide-derived oxidants by myeloperoxidase in monocytes:pathways for monocyte-mediated protein nitration and lipid peroxidn. in vivo)

IT 7722-84-1, Hydrogen peroxide, biological studies 19059-14-4, Peroxynitrite

(formation of nitric oxide-derived oxidants by myeloperoxidase in monocytes:pathways for monocyte-mediated protein nitration and lipid peroxidn. in vivo)

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ANSWER 7 OF 28 HCA COPYRIGHT 2003 ACS on STN
131:161001 Oxidative drop or aerosol separator for waste gases or
     exhaust air streams. Gernhardt, Hans Dieter; Giersbach, Gerhard;
     Zimmermann, Klaus; Tauchnitz, Heiko; Vanselow, Heike; Kretzschmar,
     Kurt; Neubert, Jens; Eichhorst, Volker (Krupp VDM G.m.b.H.,
     Germany). Ger. Offen. DE 19805444 Al 19990819, 6 pp.
     CODEN: GWXXBX. APPLICATION: DE 1998-19805444 19980211.
     A separator with catalytically active surfaces is used for removal
AB
     of drops or aerosols from gases with partial oxidn. of org. or
     inorg. contaminants, e.g., formaldehyde or NOx, in the gas or liq.
               The gas stream is sprayed with oxidizing agents, e.g., aq.
     H2O2, before entering the separator section of the unit.
     The separator section comprises catalytic metal packing or nets with
     wt. 0.05-10 \text{ kg/L} and 50\% porosity.
     10102-43-9, Nitric oxide, processes
IT
     10102-44-0, Nitrogen dioxide, processes
        (oxidative drop or aerosol separator for waste gases or
        exhaust air streams)
                HCA
RN
     10102-43-9
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
CN
N == O
     10102-44-0 HCA
RN
     Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
CN
0 - N = 0
     7722-84-1, Hydrogen peroxide, uses
IT
        (oxidizing agents; oxidative drop or aerosol separator for waste
        gases or exhaust air streams)
RN
     7722-84-1 HCA
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
HO-OH
IC
     ICM
          B01D045-10
     ICS B01D053-86; B01D053-94
     59-4 (Air Pollution and Industrial Hygiene)
CC
     Section cross-reference(s): 47, 67
     50-00-0, Formaldehyde, processes 10102-43-9,
IT
     Nitric oxide, processes 10102-44-0,
     Nitrogen dioxide, processes 11104-93-1, Nitrogen
     oxide, processes
        (oxidative drop or aerosol separator for waste gases or
        exhaust air streams)
     563-69-9, Carbonoperoxoic acid 7722-84-1, Hydrogen
IT
     peroxide, uses
        (oxidizing agents; oxidative drop or aerosol separator for waste
```

gases or exhaust air streams)

ANSWER 8 OF 28 HCA COPYRIGHT 2003 ACS on STN 129:249339 Regional-scale oxidant formation: analysis of rural and urban coupling. Lu, Cheng-Hsuan (State Univ. of New York, Albany, NY, USA). 153 pp. Avail. UMI, Order No. DA9830205 From: Diss. Abstr. Int., B 1998, 59(4), 1566 (English) 1998. AΒ Unavailable 7722-84-1, Hydrogen peroxide, reactions IT10102-43-9, Nitric oxide, reactions 10102-44-0, Nitrogen dioxide, reactions (modeling regional-scale oxidant formation by analyzing rural and urban environmental coupling) RN7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CNHO-OH RN 10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CN N = 0RN 10102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN 0 - N = 059-2 (Air Pollution and Industrial Hygiene) CC Section cross-reference(s): 53 ozone formation photochem air pollution; urban rural environmental STcoupling photochem pollution; modeling urban rural environmental coupling; odd hydrogen cycling photochem air pollution; nitric oxide oxidn nitrogen dioxide pollution; aldehyde isoprene interaction air pollution 50-00-0, Formaldehyde, reactions IT 78-79-5, Isoprene, reactions 7697-37-2, Nitric acid, reactions **7722-84-1**, Hydrogen peroxide, reactions 7727-37-9D, Nitrogen, oxygen-contg., reactions 10102-43-9, Nitric oxide, reactions 10102-44-0, Nitrogen dioxide, reactions (modeling regional-scale oxidant formation by analyzing rural and urban environmental coupling)

L55 ANSWER 9 OF 28 HCA COPYRIGHT 2003 ACS on STN 127:282532 Oxidative stress response and photosystem 2 efficiency in trees of urban areas. Rank, B. (Institute of Biology, Humboldt-University Berlin, Berlin, D-10099, Germany).

Photosynthetica, 33(3-4), 467-481 (English) 1997. CODEN: PHSYB5. ISSN: 0300-3604. Publisher: Institute of Experimental Botany, Academy of Sciences of the Czech Republic. The neophyte Ailanthus altissima (Tree of Heaven), 1751 introduced AB from China to England, is propagating in some urban areas very successfully in spite of the increasing air pollution, whereas many traditional urban trees decline. It was examd., whether this rapid spread might be supported by a high capacity of antioxidative In comparison to Betula, Tilia and Platanus, the leaves of Ailanthus had the lowest content of thiobarbiturate-reactive substances (TBA-rs) and the highest activity of ascorbate-specific peroxidase (AS-POD). This indicated a lower level of oxidative lipid breakdown and a higher capacity for detoxification of H202 in leaves of Ailanthus than in the other three species. Further on, the quantum yield of photosystem (PS) 2, .DELTA.F/Fm', was quantified by means of fluorimetric anal. Whereas no differences were found between Ailanthus, Betula and Platanus, the leaves of Tilia had a relative lower efficiency in PS2 photochem. The air analyses done by the Senat von Berlin were used to examine the influence of actual concns. of air pollutants 03, SO2 and NOx on the leaves of investigated trees. Only the leaves of Ailanthus might react on air pollution in different habitats by elevating the activity of AS-POD under high pollution, but in a very limited way. The quantum yield of PS2 and the amt. of TBA-rs in the leaves were not influenced by the concn. of air pollutants. Differences between individual trees within species can be due to the genotype or to edaphic factors, but not to the level of air pollution of the Therefore improvement of cultivation, fertilization, aeration of the soil and other measures should be helpful for the survival of urban trees even under strong immission conditions. 10102-43-9, Nitric oxide, biological IT studies 10102-44-0, Nitrogen dioxide, biological studies (oxidative stress response and photosystem 2 efficiency in trees of urban areas) 10102-43-9 HCA RN CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) N = O10102-44-0 HCA RNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN O - N = O59-2 (Air Pollution and Industrial Hygiene) CC 7446-09-5, Sulfur dioxide, biological studies 10028-15-6, Ozone, ITbiological studies 10102-43-9, Nitric oxide, biological studies 10102-44-0, Nitrogen dioxide, biological studies 11104-93-1,

Nitrogen oxide, biological studies (oxidative stress response and photosystem 2 efficiency in trees of urban areas)

L55 ANSWER 10 OF 28 HCA COPYRIGHT 2003 ACS on STN

127:15075 Dichlorodihydrofluorescein and dihydrorhodamine 123 are sensitive indicators of peroxynitrite in vitro: implications for intracellular measurement of reactive nitrogen and oxygen species. Crow, John P. (Department of Anesthesiology, University of Alabama at Birmingham, AL, 35233, USA). Nitric Oxide, 1(2), 145-157 (English) 1997. CODEN: NIOXF5. ISSN: 1089-8603. Publisher: Academic.

2,7-Dichlorodihydrofluorescein (DCDHF), commonly known as ABdichlorofluorescin, and dihydrorhodamine 123 (DHR) are often used to detect the prodn. of reactive nitrogen and oxygen species in cells via oxidn. to their resp. fluorescent products. To det. which biol. oxidants might be involved, DCDHF and DHR were exposed to a no. of oxidants in vitro to det. which are capable of oxidizing these compds. Formation of dichlorofluorescein (DCF) and rhodamine is typically monitored by measuring their intrinsic fluorescence, however, absorbance can also be utilized (.epsilon.500 nm = 59,500 and 78,800 M-1 cm-1 for DCF and rhodamine, resp.). Peroxynitrite (ONOO-) readily oxidized both compds. with an efficiency equal to Addn. of nitric oxide 38% of added ONOO- for DCDHF and 44% for DHR. (NO) to a superoxide-generating system resulted in DCDHF and DHR oxidn. which was inhibitable by superoxide dismutase (SOD). SIN-1-mediated oxidn. of DCDHF and DHR was also SOD-inhibitable, suggesting that peroxynitrite is the primary oxidant formed from SIN-1 decompn. Aerobic addn. of NO resulted in DCDHF oxidn. in a manner consistent with nitrogen dioxide (.cntdot.NO2) formation. NO did not oxidize DHR and actually inhibited UV-light-induced DHR oxidn. Simultaneous addn. of NO and ONOO- resulted in an apparent inhibition of indicator oxidn.; however, subsequent addn. of ONOO- alone 20 s later produced a higher than av. amt. of oxidized indicator. Addn. of indicator after NO + ONOO- followed by subsequent ONOO- addn. gave similar results, suggesting the formation of a relatively stable, oxidant-activated NO/ONOO- adduct. At pH 7.4, hypochlorous acid was 66% efficient at oxidizing DHR but only 9% with DCDHF. Neither **H2O2** (1 mM) nor superoxide flux alone produced significant indicator oxidn. Oxidn. of DCDHF by horseradish peroxidase (HRP) plus H202 was considerably less efficient than oxidn. of At 20-fold higher concns., HRP alone oxidized DHR but the rate was much lower than when H2O2 was present. Catalase largely inhibited HRP-mediated oxidn. of DHR but not DCDHF, suggesting a direct effect of the peroxidase on DCDHF. results reveal that peroxynitrite, hypochlorous acid, and H2O2 plus peroxidase all oxidize DCDHF and DHR to varying degrees but that neither superoxide, H2O2 alone, nor physiol. levels of nitric oxide are capable of indicator oxidn. Thus, DCDHF or DHR oxidn. in any given cell type may involve more than one oxidant. In cell systems where nitric

oxide prodn. occurs, oxidn. of either DCDHF or DHR is likely to include a peroxynitrite component. Identification of relevant oxidants will best be achieved with a combined exptl. approach which exploits the differential reactivities of DCDHF and DHR and the judicious use of inhibitors and oxidant scavengers.

7722-84-1, Hydrogen peroxide, analysis 10102-43-9, Nitric oxide, analysis 10102-44-0,

Nitrogen dioxide, analysis

(dichlorodihydrofluorescein and dihydrorhodamine 123 are sensitive indicators of reactive nitrogen and oxygen species)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O- N-O

CC 9-15 (Biochemical Methods) Section cross-reference(s): 6, 79

7722-84-1, Hydrogen peroxide, analysis
7790-92-3, Hypochlorous acid 10102-43-9, Nitric oxide,
analysis 10102-44-0, Nitrogen dioxide,
analysis 11062-77-4, Superoxide 19059-14-4, Peroxynitrite
33876-97-0, SIN-1
(dichlorodihydrofluorescein and dihydrorhodamine 123 are
sensitive indicators of reactive nitrogen and oxygen species)

L55 ANSWER 11 OF 28 HCA COPYRIGHT 2003 ACS on STN

126:242120 Hydrothermal Oxidation of Organic Wastes Using Ammonium
Nitrate. Proesmans, Petra I.; Luan, Li; Buelow, Steven J. (Chemical Science and Technology Division, Los Alamos National Laboratory, Los Alamos, NM, 87545, USA). Industrial & Engineering Chemistry
Research, 36(5), 1559-1566 (English) 1997. CODEN: IECRED. ISSN:
0888-5885. Publisher: American Chemical Society.

The use of ammonium nitrate as an oxidizing agent in hydrothermal oxidn. of org. compds. was studied. The oxidn. of model compds., methanol, acetic acid, and phenol, was studied at 500.degree. and 345 bar. High org., ammonia, and nitrate removal was achieved at stoichiometric concns. The oxidn. of ammonia by nitrate was much faster than the oxidn. of either methanol or acetic acid and only slightly faster than phenol. N products included N, N2O, and

NO2- as well as toxic NO and trace amts. of NO2. C products were CO2, HCO3-, CO32-, and CO. The co-oxidant system with H2O2 and ammonium nitrate was studied to eliminate the NOx prodn. Stoichiometric concns. of H2O2 to the C concns. resulted in undetectable NOx levels. 10102-43-9, Nitric oxide, formation IT (nonpreparative) 10102-44-0, Nitrogen dioxide, formation (nonpreparative) (hydrothermal oxidn. of org. wastes using ammonium nitrate) 10102-43-9 HCA RNNitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CN N = 010102-44-0 HCA RNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN 0-N=07722-84-1, Hydrogen peroxide, uses IT (hydrothermal oxidn. of org. wastes using ammonium nitrate) 7722-84-1 HCA RN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CNHO-OH 60-2 (Waste Treatment and Disposal) CC 630-08-0, Carbon monoxide, formation (nonpreparative) 10024-97-2, IT Nitrous oxide, formation (nonpreparative) 10102-43-9, Nitric oxide, formation (nonpreparative) 10102-44-0, Nitrogen dioxide, formation 11104-93-1, Nitrogen oxide, formation (nonpreparative) (nonpreparative) (hydrothermal oxidn. of org. wastes using ammonium nitrate) 7722-84-1, Hydrogen peroxide, uses IT(hydrothermal oxidn. of org. wastes using ammonium nitrate) ANSWER 12 OF 28 HCA COPYRIGHT 2003 ACS on STN 126:241973 Oxidation of NO to NO2 by hydrogen peroxide and its mixtures with methanol in natural gas and coal combustion gases. Zamansky, Vladimir M.; Ho, Loc; Maly, Peter M.; Seeker, W. Randall (Energy Environmental Research Corporation, Irvine, CA, 92618, USA). Combustion Science and Technology, 120(1-6), 255-272 (English) 1996. CODEN: CBSTB9. ISSN: 0010-2202. Publisher: Gordon & Breach. The CombiNOx process includes a family of NOx control technologies AΒ (reburning, urea injection, MeOH injection, and wet scrubbing)

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capable of reducing NOx from stationary combustion sources by
      .apprx.90%. However, MeOH forms CO in flue gas as a byproduct.
     H202 and H202/MeOH mixts. decrease the amt. of CO.
     Exptl. and modeling results on H202 and H202
     /MeOH reactions with NO in a 300-kW combustor firing natural gas and
     coal are presented. Max. NO oxidn. was achieved at 750-820 K for
     injection of H2O2, and 1:1 H2O2/MeOH mixt., and
     at 850-930 K for MeOH injection. NO-to-NO2 conversion of 90-98 and 64-76% was achieved at an additive NO molar ratio of 1.5
     during natural gas and coal firing, resp. Influence of initial NO
     concns., the additive/NO ratio, O and SO2 concns., and the presence
     of fly ash on process performance is discussed. Exptl. results are
     qual. explained by kinetic modeling.
     10102-43-9, Nitrogen monoxide, reactions
         (oxidn. of nitric oxide by
        hydrogen peroxide and methanol in natural gas
        and coal combustion gases)
     10102-43-9 HCA
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
N = 0
     7722-84-1, Hydrogen peroxide, reactions
         (oxidn. of nitric oxide by
        hydrogen peroxide and methanol in natural gas
        and coal combustion gases)
     7722-84-1 HCA
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
HO-OH
     59-4 (Air Pollution and Industrial Hygiene)
     Section cross-reference(s): 51
     coal flue gas nitrogen oxide oxidn; hydrogen
     peroxide methanol oxidn nitrogen oxide; firing flue gas
     nitrogen oxide oxidn
     Ashes (residues)
     Ashes (residues)
        (coal fly; oxidn. of nitric oxide
        by hydrogen peroxide and methanol in natural
        gas and coal combustion gases)
     Flue gases
        (coal, natural gas; oxidn. of nitric
        oxide by hydrogen peroxide and
        methanol in natural gas and coal combustion gases)
     Oxidation kinetics
     Simulation and Modeling, physicochemical
        (oxidn. of nitric oxide by
        hydrogen peroxide and methanol in natural gas
        and coal combustion gases)
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IT

RN

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IT 10102-43-9, Nitrogen monoxide, reactions
 (oxidn. of nitric oxide by
 hydrogen peroxide and methanol in natural gas
 and coal combustion gases)

IT 67-56-1, Methanol, reactions 7446-09-5, Sulfur dioxide, reactions 7722-84-1, Hydrogen peroxide, reactions 7782-44-7 Oxygen reactions

7782-44-7, Oxygen, reactions (oxidn. of nitric oxide by

hydrogen peroxide and methanol in natural gas
and coal combustion gases)

L55 ANSWER 13 OF 28 HCA COPYRIGHT 2003 ACS on STN

124:76024 Oxidative release of nitric oxide
accounts for guanylyl cyclase stimulating, vasodilator and
anti-platelet activity of Piloty's acid: a comparison with Angeli's
salt. Zamora, Ruben; Grzesiok, Andreas; Weber, Horst; Feelisch,
Martin (Dep. Nitric Oxide Research, Schwarz Pharma AG, Monheim,
D-40789, Germany). Biochemical Journal, 312(2), 333-9 (English)

ISSN: 0264-6021. Publisher: Portland Press. CODEN: BIJOAK. The decompn. of benzenesulfohydroxamic acid (Piloty's acid; PA) and AB some of its derivs. has been reported to yield nitroxyl ions (NO-), a species with potent vasodilator properties. In a previous study we demonstrated that the oxidative breakdown of PA results in the formation of nitric oxide (NO) and suggested that NO rather than NOmay account for its vasorelaxant properties. Using isolated aortic rings in organ baths, we now show that high concns. of cysteine potentiate the vasorelaxant response to PA, whereas responses to Angeli's salt (AS), a known generator of NO-, were almost completely These different behaviors of PA and AS are mirrored by inhibited. their distinct chemistries. By using HPLC it was shown that, at physiol. pH and in the absence of oxidizing conditions, PA is a relatively stable compd. Direct chem. detn. of NO, stimulation of sol. quanylyl cyclase, and measurement of platelet aggregation under various exptl. conditions confirmed the requirement for oxidn. to release NO from PA, and quite weak oxidants were found to be sufficient to promote this reaction. In contrast, at pH 7.4 AS decompd. rapidly to yield nitrite (NO2-) and NO-, but did not produce NO on reaction with dioxygen (O2) or hydrogen peroxide (H2O2). Thus sulfohydroxamic acids are a new class of thiol-independent NO-donors that generate NO rather than NO- under physiol. conditions.

IT 10102-43-9, Nitric oxide, biological studies

(oxidative release of nitric oxide accounts for guanylyl cyclase stimulating, vasodilator and anti-platelet activity of Piloty's acid: a comparison with Angeli's salt)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

```
CC
     1-8 (Pharmacology)
IT
     Blood platelet
     Blood vessel
         (oxidative release of nitric oxide
        accounts for guanylyl cyclase stimulating, vasodilator and
        anti-platelet activity of Piloty's acid: a comparison with
        Angeli's salt)
IT
     599-71-3, Piloty's acid 13826-64-7, Angeli's salt
        (oxidative release of nitric oxide
        accounts for guanylyl cyclase stimulating, vasodilator and
        anti-platelet activity of Piloty's acid: a comparison with
        Angeli's salt)
IT
     10102-43-9, Nitric oxide, biological
       (oxidative release of nitric oxide
        accounts for guanylyl cyclase stimulating, vasodilator and
        anti-platelet activity of Piloty's acid: a comparison with
        Angeli's salt)
     ANSWER 14 OF 28 HCA COPYRIGHT 2003 ACS on STN
          Silicon wafer oxidation. Iwamatsu, Seiichi (Seiko Epson K.
117:38453
     K., Japan). Jpn. Kokai Tokkyo Koho JP 04075354 A2 19920310 Heisei,
     2 pp.
            (Japanese). CODEN: JKXXAF. APPLICATION: JP 1990-188711
     19900717.
     A SiO2 film is manufd. by exposing Si in a gas atm. of NO2
AΒ
     , NO, N2O, SO3, H2O2, etc.
IT.
     7722-84-1, Hydrogen peroxide, reactions
     10102-43-9, Nitrogen monooxide, reactions 10102-44-0
     , Nitrogen dioxide, reactions
        (oxidn. of silicon wafer with)
RN
     7722-84-1 HCA
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
но-он
     10102-43-9 HCA
RN
CN
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
N = O
RN
     10102-44-0 HCA
CN
     Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
O-N=O
IC
     ICM H01L021-469
CC
     76-3 (Electric Phenomena)
IT
     7446-11-9, Sulfur trioxide, reactions 7722-84-1,
```

Hydrogen peroxide, reactions 10024-97-2, Dinitrogen oxide, reactions 10102-43-9, Nitrogen monooxide, reactions 10102-44-0, Nitrogen dioxide, reactions (oxidn. of silicon wafer with)

ANSWER 15 OF 28 HCA COPYRIGHT 2003 ACS on STN L55 117:3284 Formation of nitrogen oxides and citrulline upon oxidation of N.omega.-hydroxy-L-arginine by heme proteins. Boucher, J. L.; Genet, A.; Vadon, S.; Delaforge, M.; Mansuy, D. (Lab. Chim. Biochim. Pharmacol. Toxicol., Univ. Rene Descartes, Paris, 75270, Fr.). Biochemical and Biophysical Research Communications, 184(3), 1158-64 (English) 1992. CODEN: BBRCA9. ISSN: 0006-291X. Horseradish peroxidase (HRP) catalyzes the oxidn. of AB N.omega.-hydroxy-L-arginine (NOHA) by H2O2 with formation of citrulline and NO2- with initial rates of about 0.7 and 0.2 nmol per nmol HRP per min. In the same manner, cytochromes P 450 from rat liver microsomes catalyze the oxidn. of NOHA to citrulline and NO2- by cumylhydroperoxide. Inhibitors of these heme proteins (N3- and CN-'for HRP and miconazole for P 450) strongly inhibit both citrulline and NO2- formation. Rates of NOHA oxidn. by these heme proteins markedly decrease with time presumably because of their denaturation by nitrogen oxides and the formation of heme protein-iron-NO complexes. These results suggest that NO (and other nitrogen oxides) could be formed from oxidn. of NOHA by enzymes other than NO-synthases. 10102-43-9, Nitric oxide, biological studies

IT 10102-43-9, Nitric oxide, biological studies (formation of, by oxidn. of hydroxyarginine by peroxides catalyzed by cytochrome P 450 and horseradish peroxidase and other hemoproteins)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N---- O

IT 7722-84-1, Hydrogen peroxide, biological studies

(nitric oxide formation from hydroxyarginine oxidn. by horseradish peroxidase and other heme proteins in presence of)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

CC 7-6 (Enzymes)
Section cross-reference(s): 6, 13

IT 372-75-8, Citrulline 10102-43-9, Nitric oxide, biological studies 14797-65-0, Nitrite, biological studies (formation of, by oxidn. of hydroxyarginine by peroxides

catalyzed by cytochrome P 450 and horseradish peroxidase and other hemoproteins)

IT 80-15-9, Cumyl hydroperoxide

(nitric oxide formation from hydroxyarginine oxidn. by cytochrome P 450 in presence of)

IT 7722-84-1, Hydrogen peroxide, biological studies

(nitric oxide formation from hydroxyarginine oxidn. by horseradish peroxidase and other heme proteins in presence of)

L55 ANSWER 16 OF 28 HCA COPYRIGHT 2003 ACS on STN

- 114:158798 Peroxynitrite oxidation of sulfhydryls. The cytotoxic potential of superoxide and nitric oxide. Radi, Rafael; Beckman, Joseph S.; Bush, Kenneth M.; Freeman, Bruce A. (Dep. Anesthesiol., Univ. Alabama, Birmingham, AL, 35233, USA). Journal of Biological Chemistry, 266(7), 4244-50 (English) 1991. CODEN: JBCHA3. ISSN: 0021-9258.
- AB Peroxynitrite anion (ONOO-) is a potent oxidant that mediates oxidn. of both nonprotein and protein sulfhydryls. Endothelial cells, macrophages, and neutrophils can generate superoxide as well as nitric oxide, leading to the prodn. of peroxynitrite anion in vivo. Apparent second order rate consts. were 5900 M-1.s-1 and 2600-2800 M-1.s-1 for the reaction of peroxynitrite anion with free cysteine and the single thiol of albumin, resp., at pH 7.4 and 37.degree.. These rate consts. are 3 orders of magnitude greater than the corresponding rate consts. for the reaction of hydrogen peroxide with sulfhydryls at pH 7.4. Unlike H2O2, which oxidizes thiolate anion, peroxynitrite anion reacts preferentially with the undissociated form of the thiol group. Peroxynitrite oxidizes cysteine to cystine and the bovine serum albumin thiol group to an arsenite nonreducible product, suggesting oxidn. beyond sulfenic acid. Peroxynitrous acid was a less effective thiol-oxidizing agent than its anion, with oxidn. presumably mediated by the decompn. products, hydroxyl radical and nitrogen dioxide. The reactive peroxynitrite anion may exert cytotoxic effects in part by oxidizing tissue sulfhydryls.

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N----- O

IT 7722-84-1, Hydrogen peroxide, biological studies

(sulfhydryl oxidn. by, nitric oxide

- and superoxide-generated peroxynitrite anion oxidn. in

comparison with)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

CC 4-3 (Toxicology)

ST peroxynitrite oxidn sulfhydryl; superoxide nitric oxide peroxynitrite oxidn sulfhydryl

IT Mercapto group

(nitric oxide- and superoxide-generated peroxynitrite anion oxidn. of, hydrogen peroxide-mediated oxidn. in comparison with)

IT Albumins, reactions

(nitric oxide- and superoxide-generated peroxynitrite oxidn. of sulfhydryl group in, hydrogen peroxide -mediated oxidn. in comparison with)

IT Kinetics of oxidation

(of sulfhydryl, by nitric oxide- and superoxide-generated peroxynitrite anion, hydrogen peroxide-mediated oxidn. in comparison with)

IT 19059-14-4, Peroxynitrite

(nitric oxide and superoxide generation of, sulfhydryl oxidn. by, hydrogen peroxide-mediated oxidn. in comparison with)

IT 52-90-4, Cysteine, biological studies
 (oxidn. of, by nitric oxide- and
 superoxide-generated peroxynitrite anion, hydrogen
 peroxide-mediated oxidn. in comparison with)

IT 10102-43-9, Nitrogen oxide (NO), biological studies

11062-77-4, Superoxide

(peroxynitrite anion generation by, sulfhydryl oxidn. by, hydrogen peroxide-mediated oxidn. in comparison with)

TT 7722-84-1, Hydrogen peroxide, biological
studies

(sulfhydryl oxidn. by, nitric oxide
- and superoxide-generated peroxynitrite anion oxidn. in
comparison with)

L55 ANSWER 17 OF 28 HCA COPYRIGHT 2003 ACS on STN

97:187419 Behavior of methanol and formaldehyde in waste gases from methanol combustion. Effects of nitric oxide on the oxidation reaction. Yano, Toshiaki; Ito, Kenichi (Coll. Eng., Hokkaido Univ., Sapporo, Japan). Nippon Kikai Gakkai Ronbunshu, B-hen, 48(431), 1392-401 (Japanese) 1982. CODEN: NKGBDD. ISSN: 0387-5016.

AB The effect of air fuel ratio, .vphi.AF = 0.8 - 1.4, and the NO in the exhaust gas on the uncombusted MeOH and CH2O in the exhaust gas from a MeOH-burning engine were studied. The oxidn. of MeOH was fast at 1.0 - 1.2 .vphi.AF when NO concn. and O concn. are both

high. CH2O formation was the greatest at 1.4 .vphi.AF, when the O concn. is high, and the lowest at 0.8 .vphi.AF, when NO is low. IT7722-84-1, uses and miscellaneous 10102-43-9, uses and miscellaneous 10102-44-0, uses and miscellaneous (in exhaust gas from methanol-burning engines, nitric oxide in relation to) RN7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CNно-он RN 10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CNN = 010102-44-0 HCA RNCNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) O- N-O CC 59-3 (Air Pollution and Industrial Hygiene) IT 50-00-0, occurrence 67-56-1, occurrence 74-82-8, occurrence 124-38-9, occurrence 630-08-0, occurrence 1333-74-0, occurrence 2229-07-4 2465-56-7 2597-43-5 2597-44-6 3170-83-0 3352-57-6, occurrence **7722-84-1**, uses and 3315-37-5 7727-37-9, analysis 7782-44-7, occurrence miscellaneous 10024-97-2, analysis 10102-43-9, uses and 7782-77-6 miscellaneous 10102-44-0, uses and miscellaneous (in exhaust gas from methanol-burning engines, nitric oxide in relation to) ANSWER 18 OF 28 HCA COPYRIGHT 2003 ACS on STN L55 97:97550 Oxidation of nitric oxide to nitrogen dioxide in the flue gas. II. Oxidation by addition of hydrogen gas, hydrogen peroxide, formaldehyde, methane. Murakami, Nobuaki; Izumi, Jun; Shirakawa, Seiichi (Nagasaki Inst., Mitsubishi Heavy Ind., Ltd., Nagasaki, Japan). Nenryo Kyokaishi, 61(661), 329-37 (Japanese) 1982. CODEN: ISSN: 0369-3775. NENKAU. The reaction characteristics of O2-NO-H2, H2O2, HCHO AΒ [50-00-0], and CH4 [74-82-8] systems were investigated at 400-1200.degree.. In the case of H2O2 and HCHO, oxidn. of NO to NO2 occurred at [M]/[NO].apprxeq.1, but in the case of H2 and CH4, a higher value of [M]/[NO] was needed, where [M]/[NO] is molar ratio of added chems. to NO. The importance of HO2 radicals in oxidn. of NO to NO2 was recognized from the kinetic model calcn. including 22 species and 70 elementary reactions.

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IT
      10102-44-0P, preparation
         (formation of, from nitric oxide
         oxidn. in flue qas)
      10102-44-0 HCA
RN
CN
      Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)
O- N-O
IT
     7722-84-1, reactions
         (oxidn. of nitric oxide in flue gas
        by)
     7722-84-1
RN
                HCA
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
CN
HO-OH
IT
     10102-43-9, reactions
         (oxidn. of, to nitrogen dioxide, in
        flue gas)
RN
     10102-43-9 HCA
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
CN
N = O
CC
     59-4 (Air Pollution and Industrial Hygiene)
     nitric oxide oxidn flue gas;
ST
     hydrogen peroxide oxidn nitric
     oxide; formaldehyde oxidn nitric
     oxide; methane oxidn nitric
     oxide
IT
     Flue gases
        (nitric oxide oxidn. in, to
        nitrogen dioxide)
IT
     Kinetics of oxidation
        (of nitric oxide, in flue gas)
IT
     Kinetics, reaction
        (of nitric oxide, oxidn., in flue
        gas)
IT
     10102-44-0P, preparation
        (formation of, from nitric oxide
        oxidn. in flue gas)
IT
     50-00-0, reactions
                          74-82-8, reactions
                                               1333-74-0, reactions
     7722-84-1, reactions
        (oxidn. of nitric oxide in flue gas
        by)
IT
     10102-43-9, reactions
        (oxidn. of, to nitrogen dioxide, in
        flue gas)
```

- L55 ANSWER 19 OF 28 HCA COPYRIGHT 2003 ACS on STN
 96:204728 Noncatalytic reduction of nitrogen oxides. (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 57012819 A2
 19820122 Showa, 2 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP
 1980-87406 19800627.

 AB NOx is removed from flue gases by a noncatalytic oxidn.-redn.
 process in which .gtoreq.1 of O-contg. compds. and their precursors
 and(or) H2O2 are used as oxidants and NH3 is used as a
 reducing agent. Thus, flue gas contg. 103 ppm NO and 10 vol.% O was
 treated at 500-600.degree. with 105 ppm H2O2 and 212 ppm

 NH3 to give a gas contg. apprx 10 ppm NOx. The temp range is
- treated at 500-600.degree. with 105 ppm H2O2 and 212 ppm

 NH3 to give a gas contg. .apprx.10 ppm NOx. The temp. range is lower than the 800-1000.degree. required by direct redn. with NH3. The use of MeOH [67-56-1] as the oxidant in the process yielded a similar result.

 IT 7722-84-1, reactions
- (oxidn. by, of nitric oxide, prior to redn. with ammonia, in flue gas denitration)
 RN 7722-84-1 HCA
- CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

- IC B01D053-34
- CC 59-4 (Air Pollution and Industrial Hygiene)
- ST nitrogen oxide removal flue gas; noncatalytic flue gas denitration; hydrogen peroxide flue gas denitration; methanol flue gas denitration; ammonia flue gas denitration
- IT 67-56-1, reactions
 (oxidn. by, of nitric oxide
 oxidn. by, prior to redn. with ammonia, in flue gas
 denitration)
- IT **7722-84-1**, reactions
 - (oxidn. by, of nitric oxide, prior to redn. with ammonia, in flue gas denitration)

- L55 ANSWER 20 OF 28 HCA COPYRIGHT 2003 ACS on STN 96:148294 Monitoring of nitrogen oxides. (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Tokkyo Koho JP 56048059 B4 19811113 Showa, 4 pp. (Japanese). CODEN: JAXXAD. APPLICATION: JP 1975-145751 19751205.
- AB The NOx(i.e., NO and NO2) concn. in flue gas is monitored by a process in which the NO is oxidized with H2O2 to NO2 for the spectrophotometric anal. in the visible-UV range. Thus, 120 ppm NO and 6 ppm NO2 in a heavy oil-fired boiler flue gas were detd. by using 2 equiv of

Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

CN

IC G01N021-25

CC 59-1 (Air Pollution and Industrial Hygiene) Section cross-reference(s): 79

IT Flue gases
(nitrogen oxide monitoring in, by oxidn. and UV spectrophotometry of nitrogen dioxide)

IT 11104-93-1, analysis (detn. of, in boiler flue gas, by oxidn. and UV spectrophotometry of nitrogen dioxide)

TT 7722-84-1, reactions
 (oxidn. by, of nitric oxides, in
 monitoring of nitrogen oxide in flue gas, by UV
 spectrophotometry)

L55 ANSWER 21 OF 28 HCA COPYRIGHT 2003 ACS on STN 95:208862 Sampling of nitrogen oxide-containing gas. (Kawasaki Steel Corp., Japan). Jpn. Tokkyo Koho JP 56026820 B4 19810620 Showa, 3 pp. (Japanese). CODEN: JAXXAD. APPLICATION: JP 1977-13369 19770209.

NOx in flue gas is simultaneously sorbed and oxidized (NO to NO2) in a gas-sampling system designed to improve the accuracy of NOx concn. detn. and to shorten the time spent in the detn. A flask contg. aq. sorbent (contg., e.g., 0.3% H2O2 and 0.3% H2SO4) is vacuumed until the sorbent is vaporized. Predetd. amts. of O3 and the flue gas are fed in sequence to mix with the vapor in the flask. The resulting mixt. is analyzed by a conventional method.

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

IC G01N031-00; G01N001-00

CC 59-2 (Air Pollution and Industrial Hygiene) Section cross-reference(s): 79

ST nitrogen oxide detn gas sampling; flue gas nitrogen oxide; ozone
 nitric oxide oxidn app; hydrogen
 peroxide flue gas analysis

IT 7722-84-1, uses and miscellaneous (in aq. sorbent, for flue gas sampling for nitrogen oxide detn.) IT10028-15-6, reactions (nitric oxide oxidn. by, in nitrogen oxide detn. in flue gas) ANSWER 22 OF 28 HCA COPYRIGHT 2003 ACS on STN 95:171992 Formation of nitrogen dioxide by laminar Hargreaves, K. J. A.; Harvey, R.; Roper, F. G.; Smith, D. B. (London Res. Stn., Br. Gas Corp., London, SW6 2AD, UK). Symposium (International) on Combustion, [Proceedings], Volume Date 1980, 18th, 133-42 (English) 1981. CODEN: SYMCAQ. ISSN: 0082-0784. ABThe formation of NO2 assocd. with laminar flames, principally premixed CH4 [74-82-8]-air, was studied. A variety of approaches to the problem was used. Preliminary expts. by noninterfering absorption spectroscopy showed some formation of NO2 from small diffusion flames burning within an enclosed The main investigation used probe sampling and chemiluminescence anal. to yield more detailed information on the distribution of NO2 around a fuel rich premixed CH4-air The anomalous formation of NO2 in the sampling line was examd. and confirmed previous observations that in order to minimize probe-formed NO2 a low sampling pressure is essential. Under these conditions, NO2 was found at the edge of the flame and in the post flame gases. Its absence in the hot regions of the flame was in agreement with other recent work. The area immediately surrounding the burner lip is a large source of oxidizing species. However, the oxidizing potential was not fully realized, possibly due to the limited residence time of NO in this region or back reactions destroying the NO2. Evidence of the likely mechanism assocd. with the NO to NO2 conversion was obtained from measurements of H2O2 thought to be involved in the oxidn. process. The H2O2 was collected by probe sampling and condensation of flame products, followed by colorimetric anal. using TiCl4 reagent. Probe effects were again taken into consideration. Finally, a mechanism for the oxidn. of NO to NO2 is discussed. Reactive species diffuse out of the flame and react with secondary air to produce HO2 and possibly other oxidizing species. A simple computer model shows that the proposed sequence of reactions can lead to rapid oxidn. of NO. IT**10102-44-0P**, preparation (formation of, in laminar flames, mechanism of) RN10102-44-0 HCA CNNitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O-N=O

```
N = 0
CC
     50-1 (Propellants and Explosives)
ST
     nitrogen oxide methane flame; oxidn nitric
     oxide flame
IT
     Flame
         (laminar, of methane, mechanism of nitrogen
        dioxide formation in)
     74-82-8, reactions
IT
         (flames, nitrogen dioxide formation in
        laminar, mechanism of)
IT
     10102-44-0P, preparation
         (formation of, in laminar flames, mechanism of)
TΤ
     10102-43-9, reactions
         (oxidn. of, in methane laminar flames)
     ANSWER 23 OF 28 HCA COPYRIGHT 2003 ACS on STN
L55
91:78463 Oxidation of nitrogen monoxide in waste gas. Takahashi, Sadao;
     Azuhata, Shigeru; Taki, Tomoyuki; Akimoto, Hidetoshi; Hishinuma,
     Takao (Hitachi, Ltd., Japan; Babcock-Hitachi K. K.). Jpn. Kokai
     Tokkyo Koho JP 54037095 19790319 Showa, 2 pp.
                                                     (Japanese).
              APPLICATION: JP 1977-102677 19770829.
     H2O2 is added to waste gas at .gtoreq.400.degree. to
AB
     oxidize NO to NO2. The method is used for treating waste
     gas from boilers, heating furnaces, gas turbines, and combustion.
     Thus, H202 was added at H202-to-NO ratio 1.3 to
     waste gas contg. 100 ppm NO. The NO oxidn. was .qtoreq.95%.
     oxidn. is independent of O in waste gas.
IT
     7722-84-1, reactions
        (oxidn. by, of nitric oxide in
        waste gas)
RN
     7722-84-1 HCA
CN
     Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)
HO-OH
IT
     10102-43-9, reactions
        (oxidn. of, in waste gases, hydrogen
        peroxide in)
RN
     10102-43-9 HCA
CN
     Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)
N = 0
     C01B021-36; B01D053-34
IC
CC
     59-2 (Air Pollution and Industrial Hygiene)
ST
     nitric oxide oxidn hydrogen
```

peroxide; waste gas nitric oxide

oxidn

IT Waste gases

(nitric oxide in, oxidn. of,

hydrogen peroxide in)

IT **7722-84-1**, reactions

(oxidn. by, of nitric oxide in

waste gas)

IT **10102-43-9**, reactions

(oxidn. of, in waste gases, hydrogen peroxide in)

L55 ANSWER 24 OF 28 HCA COPYRIGHT 2003 ACS on STN

- 89:151861 Nitric oxide reduction in waste gases. Hayasaka, Hiroshi; Sekiguchi, Yoshitoshi; Okigami, Noboru (Hitachi Shipbuilding and Engineering Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 53033975 19780330 Showa, 3 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1976-109206 19760909.
- AB A flue gas at 400-800.degree. is contacted with .gtoreq.1 alc. (EtOH or MeOH), aldehyde (HCHO, MeCHO), or H2O2 to convert NO to NO2, (HNO)2, or HNO2 in the presence of O. Then the treated gas is scrubbed with a urea soln. For example, a flue gas contg. NO, H2O, O, and N was treated with H2O2 then scrubbed with a urea [57-13-6] soln. The NO removal was .gtoreq.90%.

IT 10102-43-9, uses and miscellaneous (removal of, from flue gas, hydrogen peroxide and urea in)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N=== O

IT 7722-84-1, uses and miscellaneous

(scrubbing soln. contg., in nitrogen oxide removal from flue gas)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

но-он

IC B01D053-34

CC 59-2 (Air Pollution and Industrial Hygiene)

ST **nitric oxide oxidn** flue gas; urea flue gas scrubbing

IT Flue gases

(nitrogen oxide removal from, hydrogen peroxide and urea scrubbing soln. for)

IT 10102-43-9, uses and miscellaneous

(removal of, from flue gas, hydrogen peroxide and urea in)

IT 57-13-6, uses and miscellaneous **7722-84-1**, uses and miscellaneous

(scrubbing soln. contg., in nitrogen oxide removal from flue gas)

ANSWER 25 OF 28 HCA COPYRIGHT 2003 ACS on STN 89:48326 Nitrogen oxide reduction. Izumi, Osamu; Murakami, Nobuaki; Shirakawa, Seiichi (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 52138053 19771117 Showa, 7 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1976-54295 19760514.

AΒ NO in flue gas is oxidized to NO2 with H2O2, then scrubbed with a urea soln. to form N and HNO3. The NHO3 soln. is vaporized and reduced to N by N2H4.

IT7722-84-1, reactions (oxidn. by, of nitric oxide in flue gases)

RN7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

IT10102-43-9, uses and miscellaneous (removal of, from flue gas, scrubbing soln. for) RN

10102-43-9 HCA

CNNitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

IC B01D053-34

CC59-2 (Air Pollution and Industrial Hygiene)

ST nitric oxide removal flue gas; hydrogen peroxide oxidn nitric oxide; urea denitrification flue gas

IT Flue gases

(nitric oxide removal from, by oxidn . with hydrogen peroxide)

IT**7722-84-1**, reactions

(oxidn. by, of nitric oxide in flue gases)

IT10102-43-9, uses and miscellaneous (removal of, from flue gas, scrubbing soln. for)

IT 57-13-6, uses and miscellaneous (scrubbing by, of nitrogen dioxide from flue gases)

ANSWER 26 OF 28 HCA COPYRIGHT 2003 ACS on STN 87:205903 Control of nitrogen oxides in waste gases. Izumi, Jun; Murakami, Nobuaki (Mitsubishi Heavy Industries, Ltd., Japan). Offen. DE 2703882 19770804, 12 pp. (German). CODEN: GWXXBX. APPLICATION: DE 1977-2703882 19770131.

ABNOx in waste gases contg. 1-10% O is controlled by mixing MeOH [67-56-1], HCHO [50-00-0], or similar O-contg. hydrocarbons, or their precursors followed by oxidn. at .ltoreg.1500.degree. to

convert NO to NO2, and scrubbing with aq. Na2SO3 (pH .gtoreq.5) to remove NO2. The oxidn. of NO to NO2 affected by H2O2 and activated O, formed as intermediate products in the oxidn. zone.

IC B01D053-34

CC 59-2 (Air Pollution and Industrial Hygiene)

IT 50-00-0, uses and miscellaneous (in **nitric oxide oxidn**., in waste gases)

IT 67-56-1, uses and miscellaneous (in **nitric oxide oxidn**.,in waste gases)

L55 ANSWER 27 OF 28 HCA COPYRIGHT 2003 ACS on STN 87:43539 Nitric oxide removal from combustion waste gas. Murakami, Nobuaki; Izumi, Jun; Shirakawa, Seiichi (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 52038460 19770325 Showa, 5 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1975-113752 19750922.

AB A NO-contg. combustion gas is mixed with H2O2 soln. to oxidize NO to NO2 at .gtoreq.150.degree., optionally a residual NO is oxidized with O3, and the NO2 is scrubbed. Thus, a waste gas contg. NO 123 ppm was bubbled through 17% H2O2 soln. at 50.degree., then passed through a reactor at .apprx.450.degree., and the gas was scrubbed. The treated gas contained .ltoreq.2 ppm NO2.

IT **7722-84-1**, reactions

(oxidn. by, of nitrogen oxide from combustion gases)

RN 7722-84-1 HCA

CN Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME)

HO-OH

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N---- O

IC B01D053-34

CC 59-2 (Air Pollution and Industrial Hygiene)

ST nitric oxide oxidn hydrogen peroxide

IT Combustion gases

(nitrogen oxide removal from, by oxidn. with hydrogen peroxide)

IT **7722-84-1**, reactions

(oxidn. by, of nitrogen oxide from combustion gases)

L55 ANSWER 28 OF 28 HCA COPYRIGHT 2003 ACS on STN 84:21675 Removal of NOx and SO2 from waste gas. Aksukawa, Masumi; Atsukawa, Masumi; Takahashi, Naoyuki; Seto, Toru (Mitsubishi Heavy Industries, Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 50070268 19750611 Showa, 6 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1973-120579 19731026.

AB A system is developed which removes NOx and SOx simultaneously and produces H2SO4 [7664-93-9] and gypsum [13397-24-5] without forming any waste water. SO2 [7446-09-5] is scrubbed with soln. contg. NaOH and Na2SO3; NO [10102-43-9] is oxidized by H2O2 and HNO3; and the NO2 [10102-44-0] formed by the oxidn. was removed by Na2SO3, producing Na2SO4. The Na2SO4 is converted to H2SO4 by electrodialysis. The Na2SO3 produced by the desulfurization is treated with Ca(OH)2 to form CaSO3 which is oxidized to CaSO4. For the treatment of a gas contg. NO 145, SO2 800 ppm, O 3%, N, CO2, and H2O balance, 15 wt.% Na2SO3 was used for desulfurization, and 5 wt.% H2O2 aq. soln. with 5 wt.% NaOH for the NO oxidn. The absorbent used for desulfurization was recycled for the removal of NO2. The concn. of NO and SO2 in the treated gas was 15 and 10 ppm, resp. Approx. 85% of the Na2SO4 was converted to HSO4.

IT 10102-43-9, uses and miscellaneous 10102-44-0, uses and miscellaneous

(removal of sulfur dioxide and, from waste gas with gypsum and sulfuric acid manuf.)

RN 10102-43-9 HCA

CN Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME)

N = 0

RN 10102-44-0 HCA

CN Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME)

O - N = O

IC B01D; C01B; C01F

CC 59-2 (Air Pollution and Industrial Hygiene)

IT 10102-43-9, uses and miscellaneous 10102-44-0, uses and miscellaneous

(removal of sulfur dioxide and, from waste gas with gypsum and sulfuric acid manuf.)

=> d 156 1-9 ti

L56 ANSWER 1 OF 9 HCA COPYRIGHT 2003 ACS on STN

- TI Method for fabricating semiconductor device to prevent contact plug damage due to misalignment
- L56 ANSWER 2 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Comparison of methods for reducing nitrogen oxides and hydrogen fluoride emissions during mixed acids pickling
- L56 ANSWER 3 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Process and apparatus for removing nitrogen and sulfur oxides from combustion gases
- L56 ANSWER 4 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Method for separation of nitrogen oxides from waste gases
- L56 ANSWER 5 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI An investigation of the adsorption of oxides of nitrogen on respirable mineral dusts and the effects on their cytotoxicity
- L56 ANSWER 6 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Flowing afterglow studies of gas phase magnesium ion chemistry
- L56 ANSWER 7 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Magnesium ion chemistry in the stratosphere
- L56 ANSWER 8 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Bond energy terms in oxides and oxo-anions
- L56 ANSWER 9 OF 9 HCA COPYRIGHT 2003 ACS on STN
- TI Catalytic reduction of nitrogen oxides with ammonia
- => d 156 3,4 cbib abs hitstr hitind
- L56 ANSWER 3 OF 9 HCA COPYRIGHT 2003 ACS on STN
- 121:237621 Process and apparatus for removing nitrogen and sulfur oxides from combustion gases. Jones, Dale G. (Noell, Inc., USA). Can. CA 1330252 Al 19940621, 69 pp. (English). CODEN: CAXXA4. APPLICATION: CA 1986-522496 19861107.
- The app. comprises an NO conversion section and an absorption section, where the section for converting NO to NO2 has a flow path for gas and a gas contacting section; means for introducing a gas contg. NO and NO2 at a first NO/ NO2 molar ratio into the contacting section; and means with preheater for mixing together a peroxyl initiator and an O-contg. gas and for injecting the mixt. into the contacting section. The preheater preheats the injection fluid, which comprises propane and oxygen in the range of 5% to 20% by vol., based on the total vol. of the injection fluid, to a temp. in the range of ambient temp. to 800.degree.F.
- IT 1344-28-1, Alumina, processes 7722-84-1, Hydrogen peroxide, processes

(process and app. for removing nitrogen and sulfur oxides from

combustion gases) 1344-28-1 HCA RN Aluminum oxide (Al2O3) (8CI, 9CI) (CA INDEX NAME) CNSTRUCTURE DIAGRAM IS NOT AVAILABLE *** 7722-84-1 RN HCAHydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CNHO-OH 10102-43-9, Nitrogen oxide (NO), processes IT 10102-44-0, Nitrogen dioxide, processes (process and app. for removing nitrogen and sulfur oxides from combustion gases) RN 10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CNN = 0RN10102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN O-M = OIC ICM B01J019-24 ICS B01D053-34; C01B021-22 59-4 (Air Pollution and Industrial Hygiene) CC 67-56-1, Methanol, processes 74-82-8, Methane, processes IT 74-84-0, Ethane, processes 74-98-6, Propane, processes Sodium carbonate, processes 1310-73-2, Sodium hydroxide, processes 1333-74-0, Hydrogen, processes 1344-28-1, Alumina , processes 7722-84-1, Hydrogen peroxide 15243-87-5, Trona 15752-47-3, Nahcolite , processes (process and app. for removing nitrogen and sulfur oxides from combustion gases) 7446-09-5, Sulfur dioxide, processes 10102-43-9, Nitrogen IT oxide (NO), processes 10102-44-0, Nitrogen dioxide, processes 11104-93-1, Nitrogen oxides, processes 12624-32-7, Sulfur oxide (process and app. for removing nitrogen and sulfur oxides from combustion gases) ANSWER 4 OF 9 HCA COPYRIGHT 2003 ACS on STN 111:139749 Method for separation of nitrogen oxides from waste gases. Mangold, Klaus; Taetzner, Carl W. (Fed. Rep. Ger.). Ger. Offen. DE 3731899 A1 19890427, 6 pp. (German). CODEN: GWXXBX. APPLICATION: DE 1987-3731899 19870923.

NOx is removed from waste gases, flue gases, or exhaust gases by treatment of the gas with an oxidizing agent (O2, O5, ${\tt H2O2}$

) to oxidize NO to NO2 at 20-200.degree. and then

AB

contacting the oxidized gas with MnO2 to form Mn(NO3)2.

The MnO2 is

in a reactive form such as granulated pyrolusite which can also contain catalytic Fe oxides such as The MnO2 can be thermally regenerated for recycling. 7722-84-1P, Hydrogen peroxide, ITpreparation (nitrogen oxide oxidn. with, in removal of nitrogen oxides from waste gases with manganese dioxide) RN7722-84-1 HCA Hydrogen peroxide (H2O2) (9CI) (CA INDEX NAME) CN HO-OH 10102-43-9, Nitrogen oxide (NO), uses and miscellaneous IT 10102-44-0, Nitrogen dioxide (NO2), uses and miscellaneous (removal of, from waste gases, with manganese dioxide) RN 10102-43-9 HCA Nitrogen oxide (NO) (8CI, 9CI) (CA INDEX NAME) CNN == ORN 10102-44-0 HCA Nitrogen oxide (NO2) (8CI, 9CI) (CA INDEX NAME) CN O - N = OIC ICM B01D053-34 C01G045-08; C01G045-02; F23J015-00 ICS ICA A62D003-00 59-4 (Air Pollution and Industrial Hygiene) CC nitrogen oxide removal waste qas; manganese dioxide nitrogen oxide STremoval; pyrolusite nitrogen dioxide removal gas 7722-84-1P, Hydrogen peroxide, IT 7782-44-7P, Oxygen, preparation 10028-15-6P, Ozone, preparation preparation (nitrogen oxide oxidn. with, in removal of nitrogen oxides from waste gases with manganese dioxide) 10102-43-9, Nitrogen oxide (NO), uses and miscellaneous IT10102-44-0, Nitrogen dioxide (11104-93-1, Nitrogen oxide, NO2), uses and miscellaneous uses and miscellaneous (removal of, from waste gases, with manganese dioxide)